

# **Design and fabrication of high performance thermoelectric modules**

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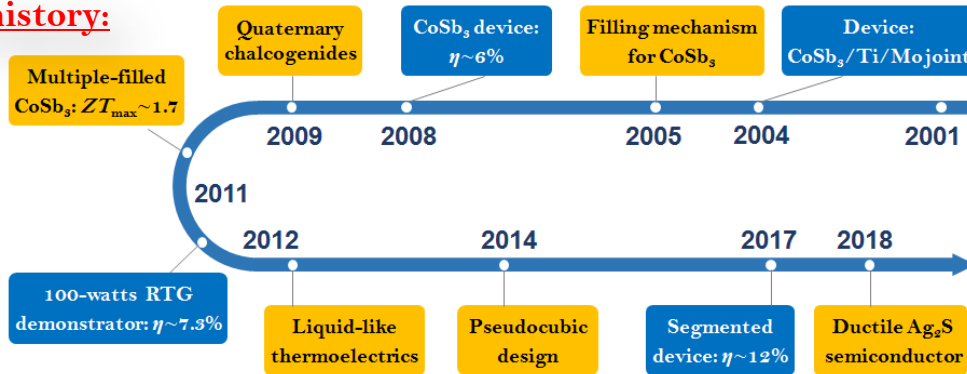
# Outline

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- 1. Brief introduction to SICCAS TE group**
- 2. Current status of thermoelectric modules**
- 3. Topologic design of TEG modules**
- 4. Interface design of TEG modules**
- 5. Performance & service behavior testing**
- 6. Summary**

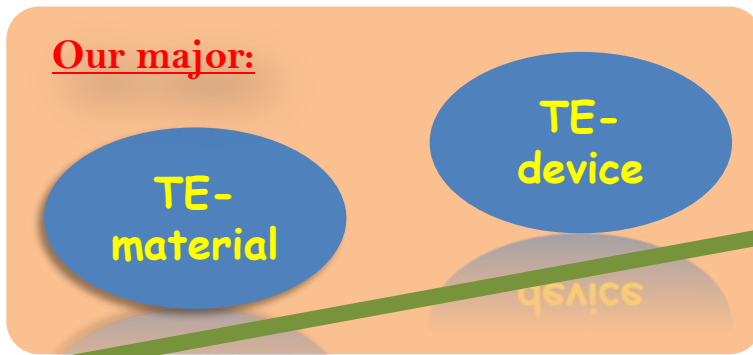
# Our goal : Full chain TE technology development

## Our history:



- 17+ years research history
- Focus on TE materials & devices
- Full chain technology development
- World-wide cooperation

## Our major:



# 22 Staffs : Multiple Disciplinary Team

## Team Leader



*Prof. Lidong Chen*

## Fundamental Research Leader



*Prof. Xun Shi*

## Engineering Research Leader



*Prof. Shengqiang Bai*

<b>Qin Yao</b>	<i>Associate Prof.</i>	<b>Organic TE</b>	<b>Jiehua Wu</b>	<i>Associate Prof.</i>	<b>Service behavior</b>
<b>Pengfei Qiu</b>	<i>Associate Prof.</i>	<b>Inorganic TE</b>	<b>Xugui Xia</b>	<i>Senior Engineer</i>	<b>Device integration</b>
<b>Ruiheng Liu</b>	<i>Associate Prof.</i>	<b>TE application</b>	<b>Ting Wu</b>	<i>Senior Engineer</i>	<b>Industrialization</b>
<b>Sanyin Qu</b>	<i>Research Assistant</i>	<b>Organic TE</b>	<b>Junqiang Song</b>	<i>Research Assistant</i>	<b>Industrialization</b>
<b>Tianran Wei</b>	<i>Research Assistant</i>	<b>Inorganic TE</b>	<b>Jincheng Liao</b>	<i>Engineer</i>	<b>Device measurement</b>
<b>Qihao Zhang</b>	<i>Research Assistant</i>	<b>Device design</b>	<b>Ming Gu</b>	<i>Engineer</i>	<b>Service behavior</b>
<b>Minghui Wang</b>	<i>Secretary</i>		<b>Chao Wang</b>	<i>Engineer</i>	<b>Device integration</b>
<b>Dudi Ren</b>	<i>Technician</i>		<b>Tingting Yang</b>	<i>Technician</i>	
<b>Jie Xiao</b>	<i>Technician</i>		<b>Hongxiu Zhou</b>	<i>Technician</i>	

~30 Ph. D. / Master candidates in TE group

# Platform: Support TE design, fabrication, measurements



Total Lab area: ~1500 m<sup>2</sup> ( in SICCAS Jiading campus )

- ❑ Synthesis & performances evaluations for TE materials: **4K ~ 1100K**
- ❑ Fabrication & performances evaluations for TE modules: **R.T. ~ 1200K**
- ❑ Mass production of bulk materials (SKD, HH, SG, ... ): **~50 kg/year**
- ❑ Mass production of Bi<sub>2</sub>Te<sub>3</sub>- & SKD-based TEG modules: **~ 10 kW/year**
- ❑ Measurement standards for TE materials & modules: **IEA-AMT member**



材料合成  
(Materials preparation)



热处理  
(Melting & annealing)



材料加工  
(Materials & module)



材料切割  
(Elements)



接触电阻测试  
(Element testing)



材料性能测试  
(Material testing)



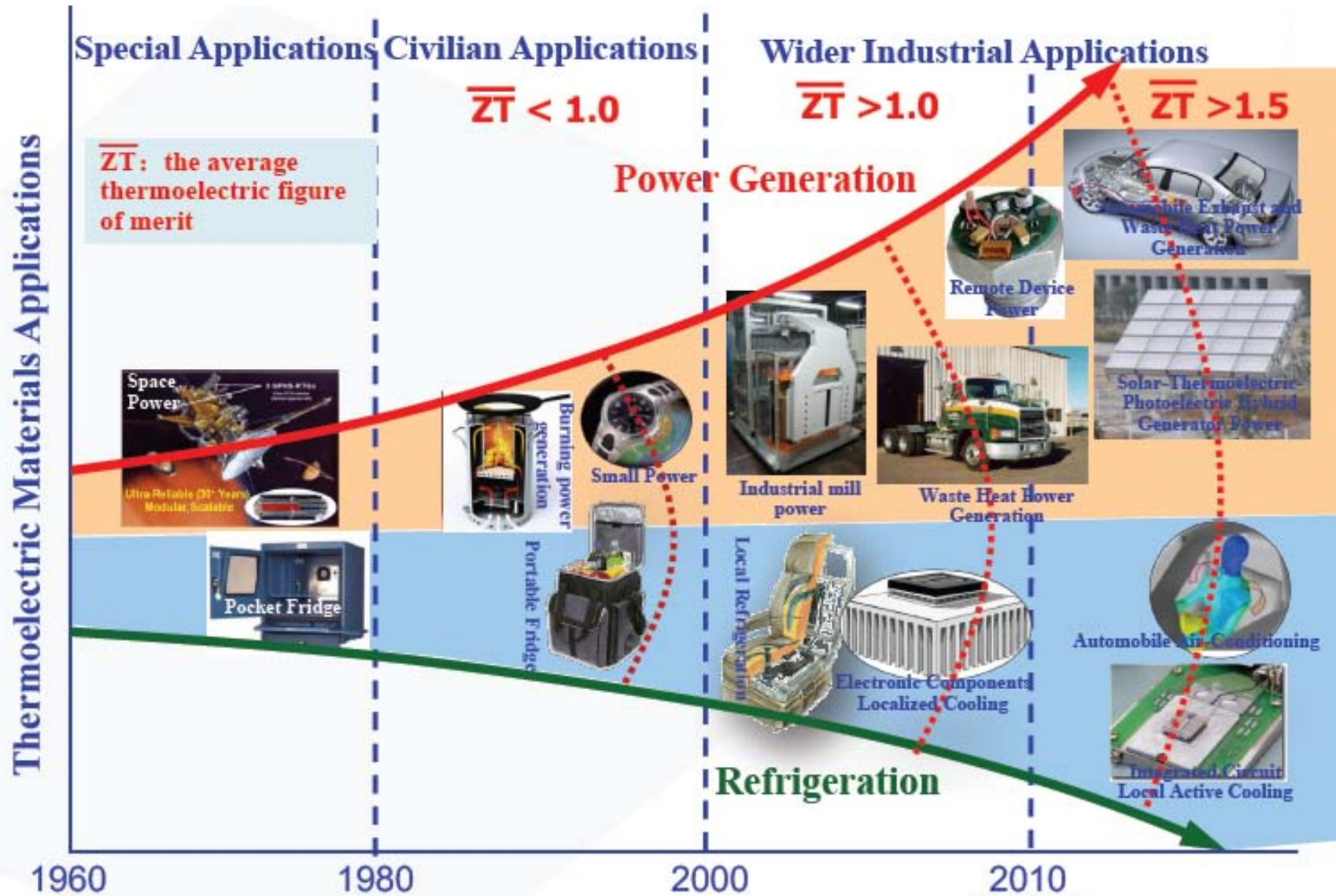
器件性能测试  
(Module testing)



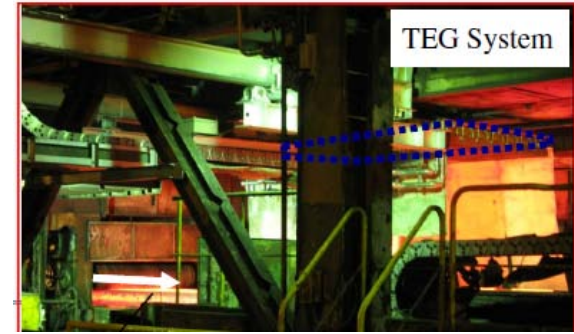
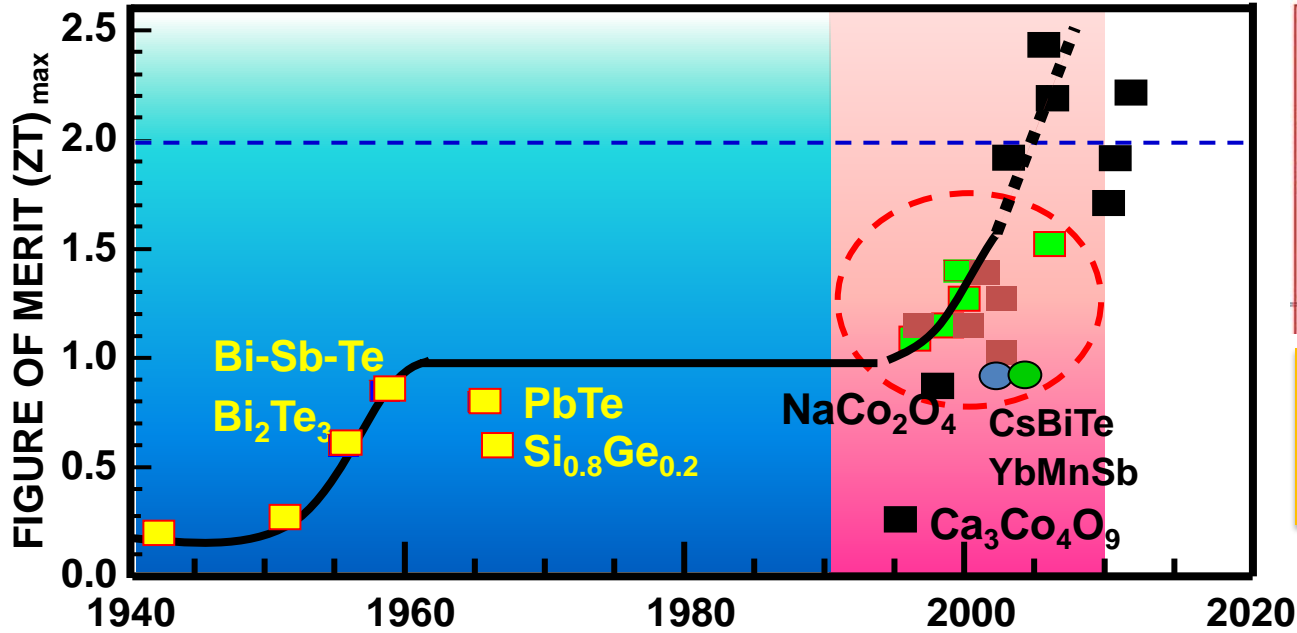
材料烧结  
(Sintering)



# TE materials applications: Wider with $ZT$ value improving



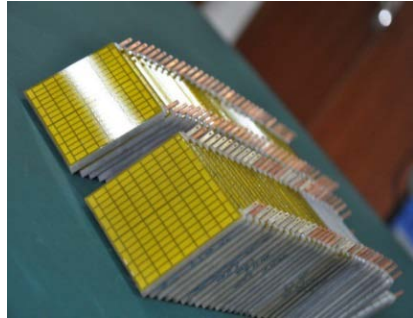
# TE module: The bridge connect material and application



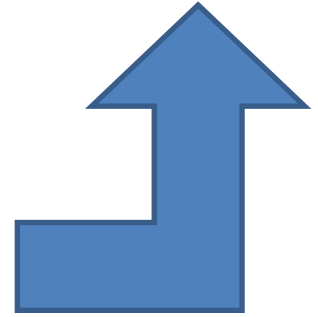
TEG system integration & industrial application

Developed TE transport theory & control strategy

High ZT value TE materials & new synthesis methods



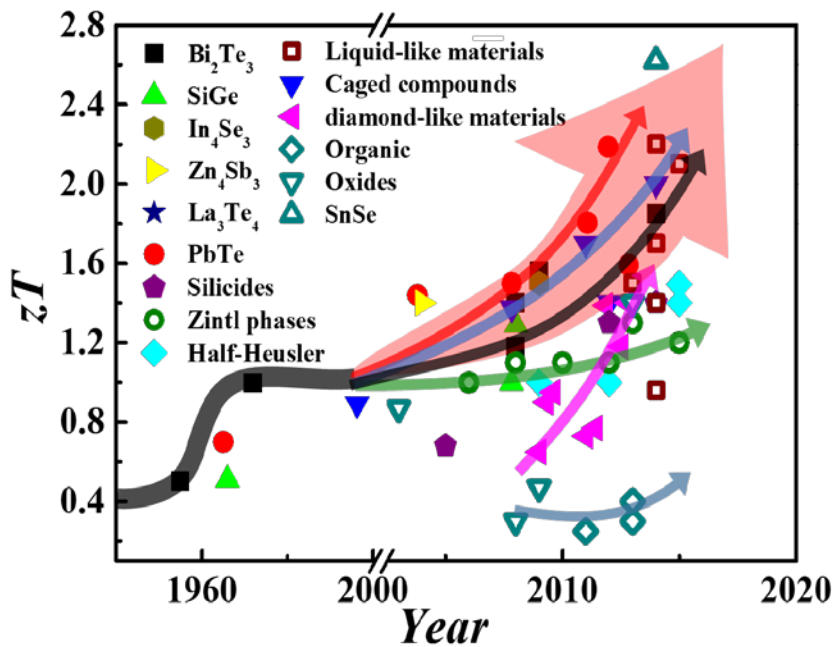
TE module design & fabrication



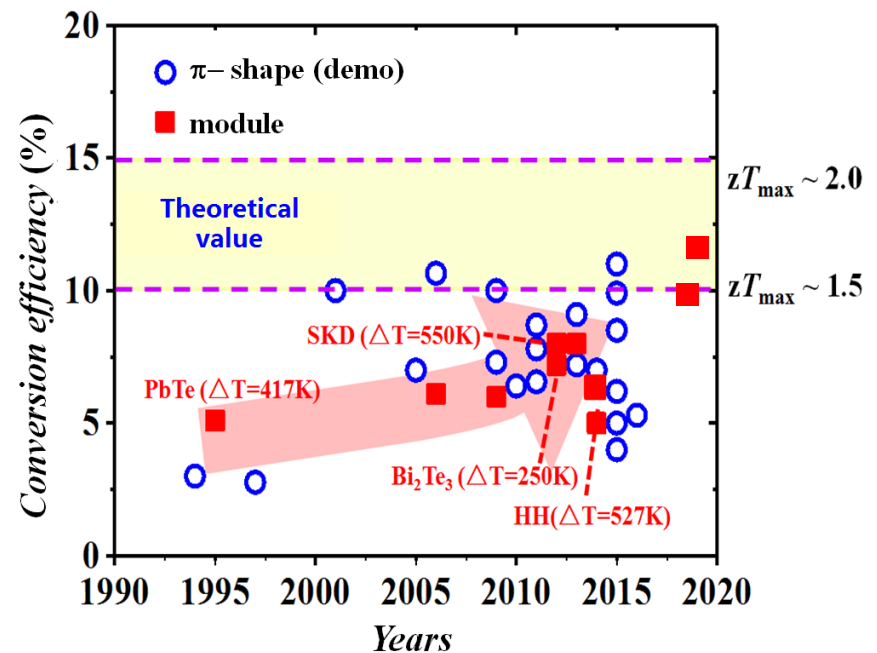
- ◆ High efficiency
- ◆ High reliability
- ◆ Low cost

# Development history of TE materials & modules

- ◆ The continuous enhancement of TE materials performance enable the widespread practical applications. (Theoretical efficiency: 10 ~ 15%)
- ◆ Nevertheless, actual TE module development has remained stagnant with rather poor efficiencies. (Actual efficiency: 5%-8%)
- ◆ More than 70% researches focus on the validation of material performance (1 leg or  $\pi$ -shape).
- ◆ TE module full chain technology including “Design – Fabrication - Evaluation” NOT established.



TE materials



TE modules



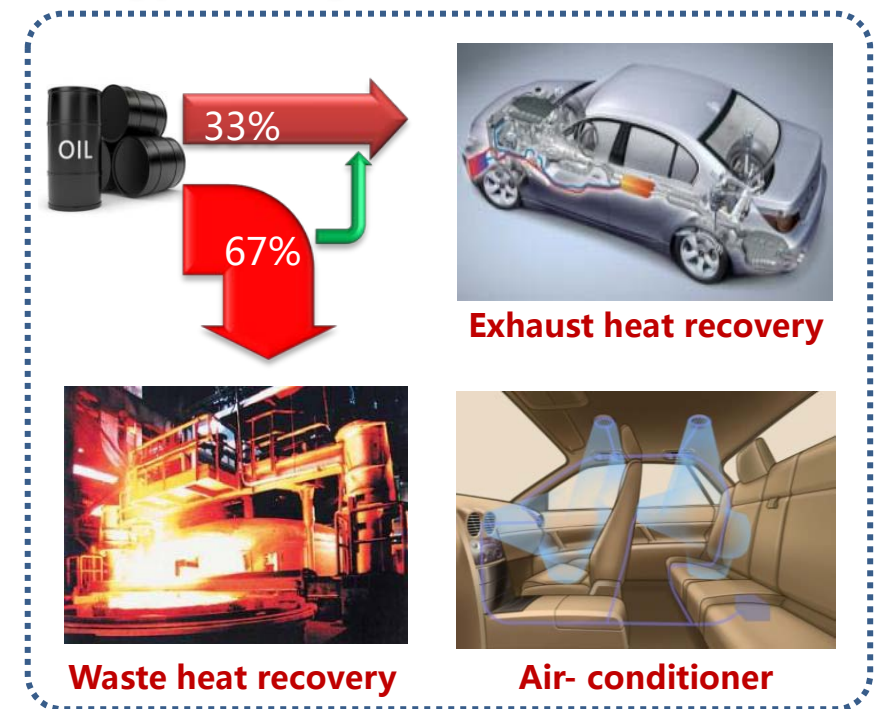
# Current status of TE modules for power generation

	Producer	TE materials	Efficiency	Source
<b>Low-T.</b>	KELK	$\text{Bi}_2\text{Te}_3$	7.2 %	JEMs-2014
	Marlow	$\text{Bi}_2\text{Te}_3$	5.03 %	Website
	Thermonamic	$\text{Bi}_2\text{Te}_3$	5 %	Website
	Hi-Z	$\text{Bi}_2\text{Te}_3$	4.5 %	Website
	Ferrotec	$\text{Bi}_2\text{Te}_3$	5 %	
	ITRI	$\text{Bi}_2\text{Te}_3$	5 %	
	SICCAS	$\text{Bi}_2\text{Te}_3$	6 %	
<b>High-T.</b>	Marlow	skutterudite	N/A	JEMs-2013
	Furukawa	skutterudite	8 %	JEMs-2012
	SICCAS	skutterudite	9.8 %	
	SICCAS	segmented	12 %	EES-2017
	AIST	segmented	11 %	
	Fraunhofer	Half-Heusler	5.4 %	
	GMZ	Half-Heusler	4.5 %	Website
	SICCAS	Half-Heusler	6.2 %	NC-2015

Industrial application requirement:

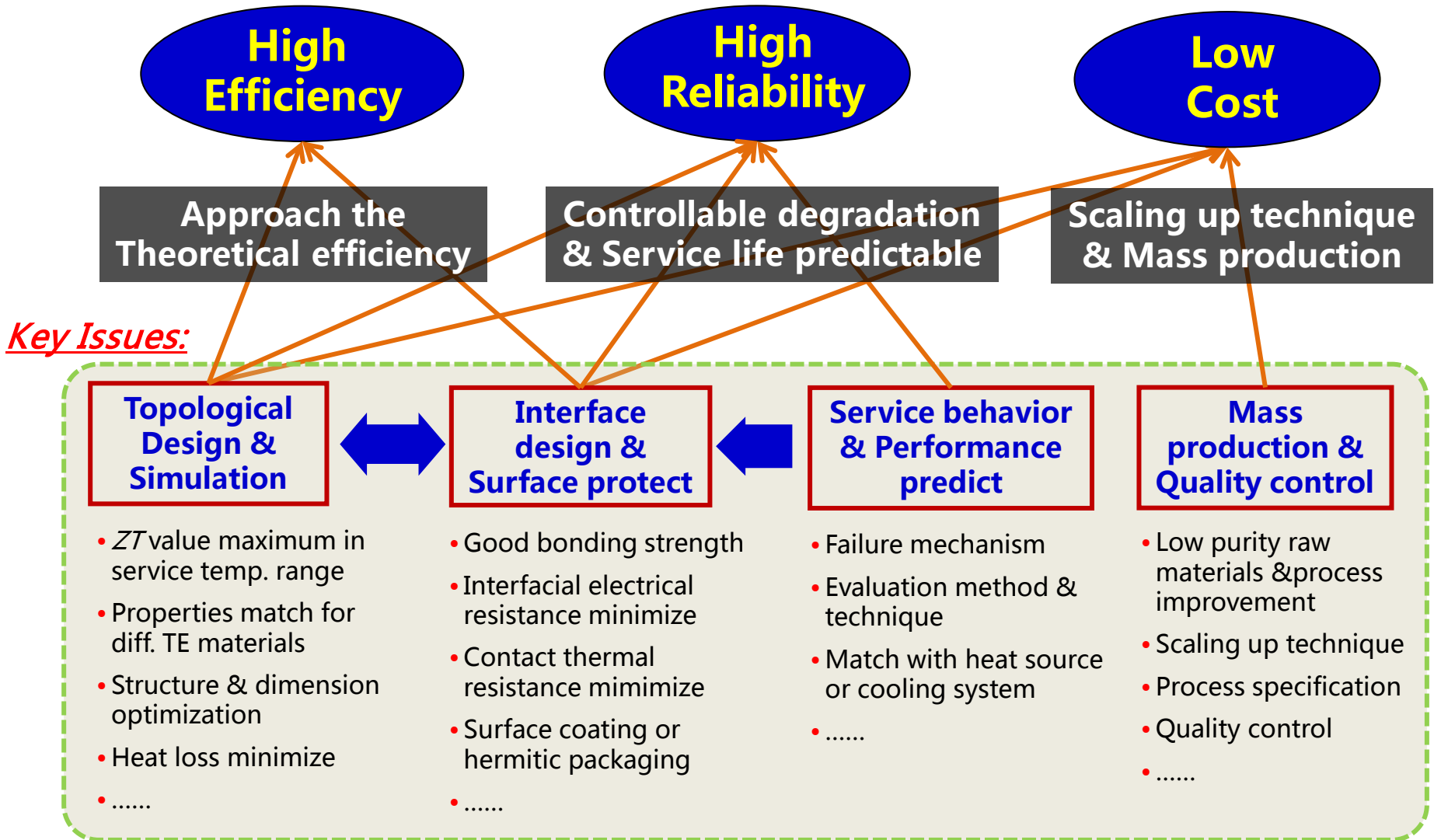
- ◆ Conversion efficiency: >10%
- ◆ Service life: > 10 years

## Energy saving & Emission reduction

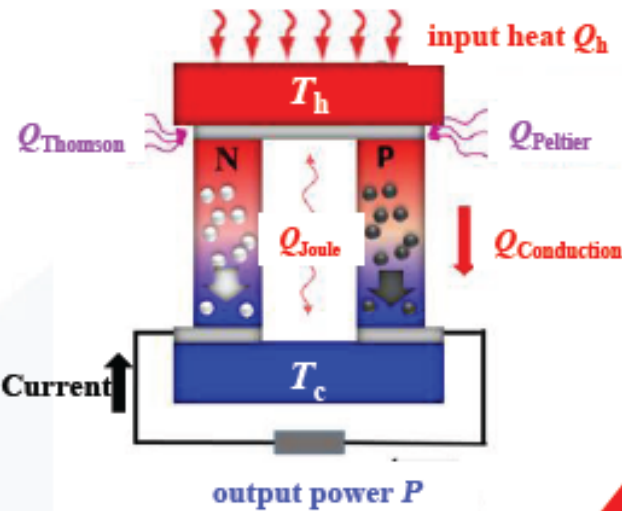


**Low efficiency & high cost** is the bottleneck of TEG in industrial application

# The targets of development of TE modules



# The principle of TE device structure design



$$\eta_{\text{theory}} = \frac{P}{Q_h} = \frac{P}{Q_{\text{Conduction}} + Q_{\text{Peltier}} - Q_{\text{Joule}} - Q_{\text{Thomson}}} = \dots$$

$$= \frac{T_h - T_c}{T_h} \cdot \frac{\frac{m}{m+1}}{1 + \frac{KR}{S^2} \frac{m+1}{T_h} - \frac{1}{2} \cdot \frac{T_h - T_c}{T_h} \cdot \frac{1}{m+1}}$$

**working  
condition**

**internal  
factor**

**➤ To minimize  $KR/S^2$**

$$\eta = \frac{T_H - T_C}{T_H} \frac{\sqrt{1 + ZT} - 1}{\sqrt{1 + ZT + T_C / T_H}}$$

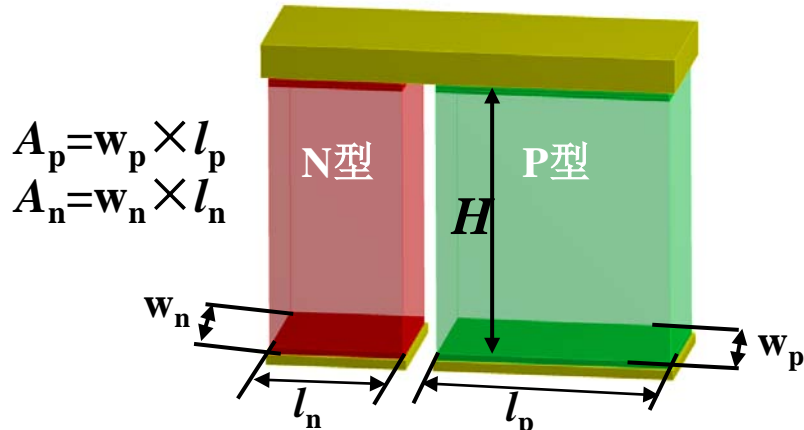
**Simplified  
mode**

$$\frac{KR}{S^2} = \frac{\kappa_n(T)\rho_n(T) + \kappa_n(T)\rho_p(T)\xi + \frac{\kappa_p(T)\rho_n(T)}{\xi} + \kappa_p(T)\rho_p(T)}{(\alpha_p(T) - \alpha_n(T))^2}$$

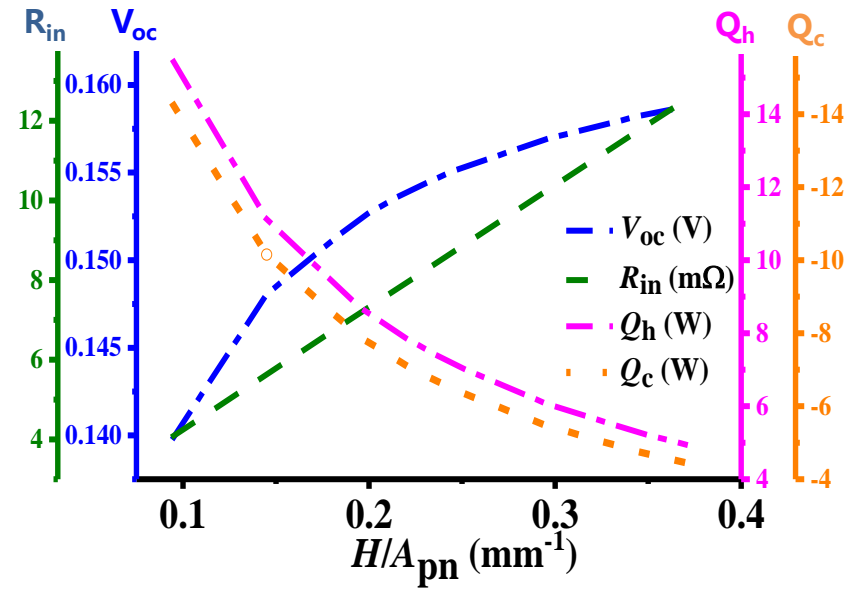
- ◆  $\kappa$ ,  $\rho$  and  $\alpha$  are temperature-dependent
- ◆ Geometry factor  $\xi$ : related to the height & cross-sectional area of TE leg
- ◆  $\xi$  can not be simply optimized when  $\kappa$ ,  $\rho$  and  $\alpha$  are temperature-dependent

# Topologic design: A useful tool to realize high efficiency

## Structure & Dimension affect on Performance



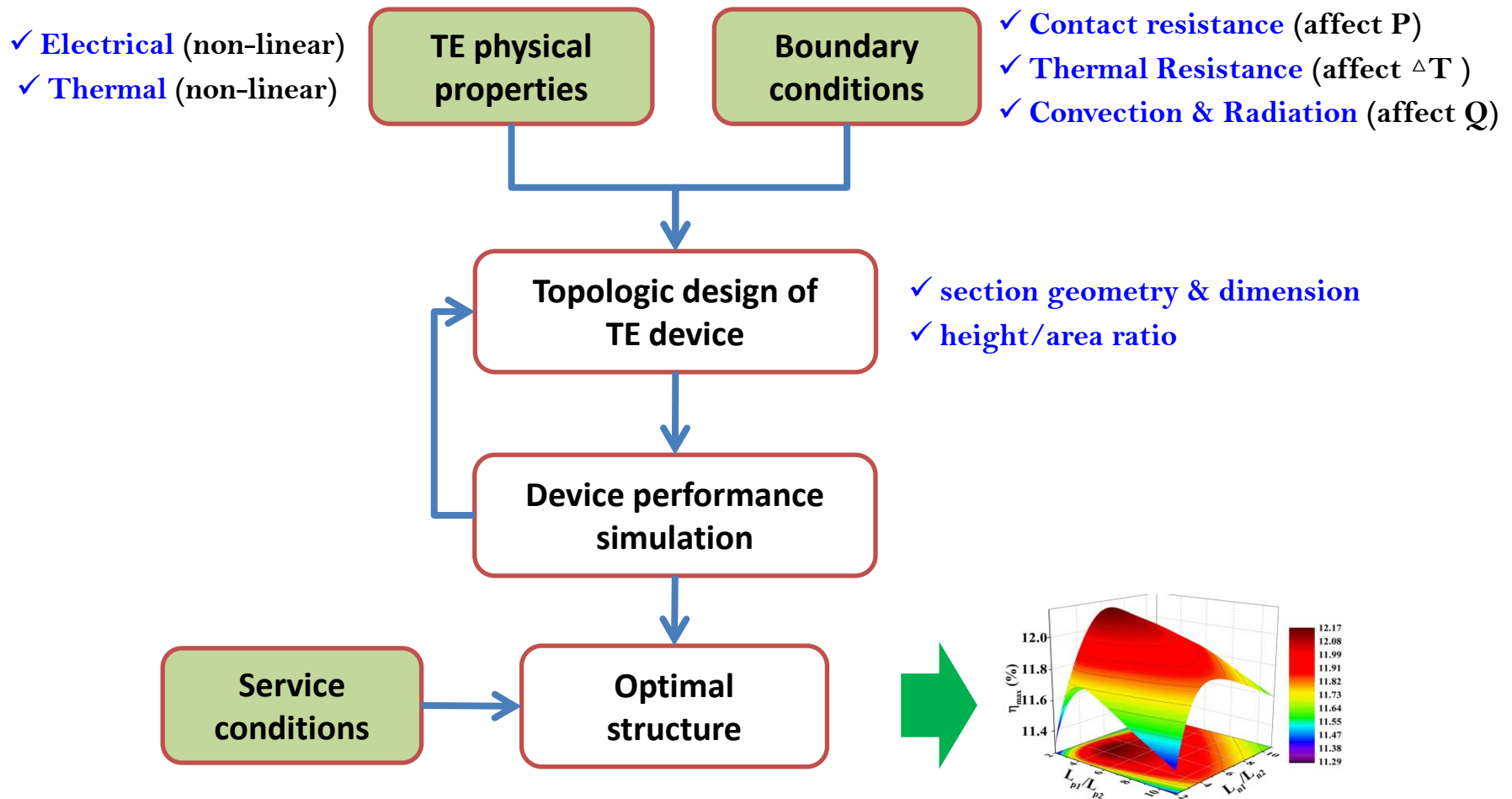
Structure factor: height, area, geometry, filling fraction



## Traditional design approach:

Model	Principle	Solution method	Influence factors					Device conversion efficiency		
			effective $\Delta T$	$(\alpha, \sigma, \kappa)$ vs T	structure factor	electric loss	thermal loss	predicted	measured	deviation
Energy balance	Global thermal equilibrium equation	algebra	✗	averaging	$A_p/A_n$	✗	✗	11.9%	8.4%	42%
One-dimensional	Local energy balance differential equation	analytical	✗	T-dependent	$A_p/A_n$	✗	✗	10.8%		29%

# Design flow of device topologic optimization



## Goal

- ◆ “Structure – performance” relationship (“TE device genetic map”)
- ◆ Full-parameter design based on service conditions



# Three-dimensional Numerical modeling

## Finite element method :

① Thermoelectric coupling constitutive equation :

$$\mathbf{q} = \alpha T \mathbf{J} - \lambda \nabla T$$

$$\mathbf{J} = -\sigma(\nabla V + \alpha \nabla T)$$

② Energy conservation equation & Charge continuity equation under steady state

$$\nabla \cdot \mathbf{q} = \dot{q}$$

$$\nabla \cdot \mathbf{J} = 0$$

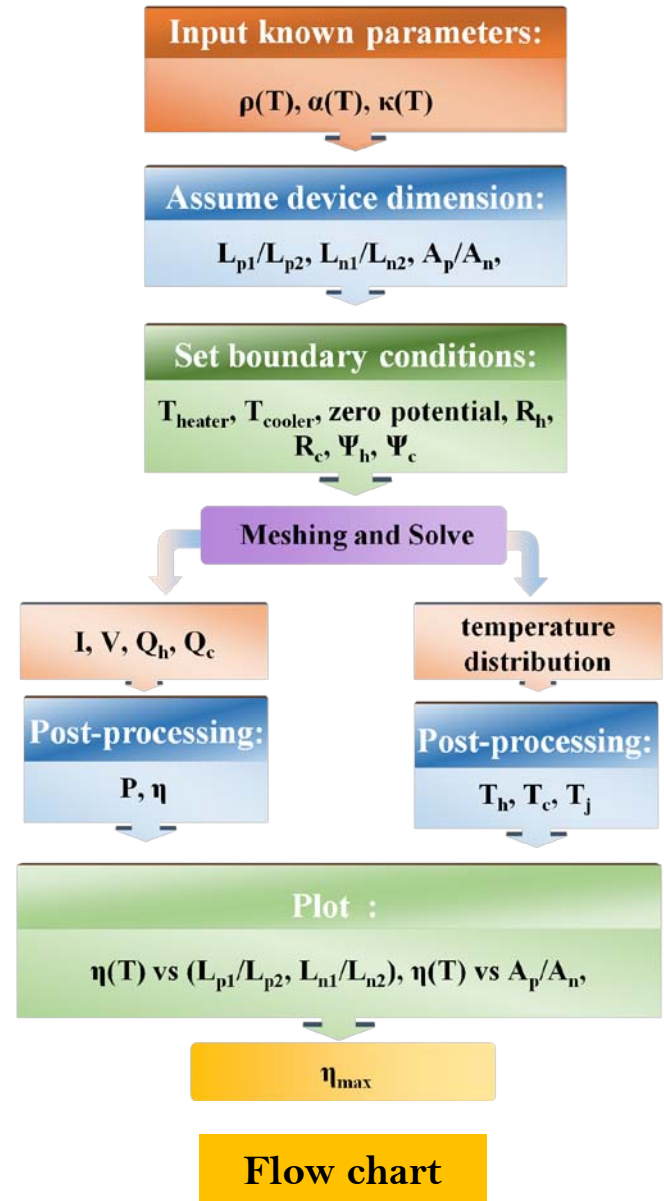
③ Governing equation describing the temperature, potential distribution & thermal-electrical coupling

$$\nabla(\lambda \nabla T) + \frac{J^2}{\sigma} - T \mathbf{J} \cdot \left[ \left( \frac{\partial \alpha}{\partial T} \right) \nabla T + (\nabla \alpha)_T \right] = 0$$

$$\nabla \cdot ([\sigma] \nabla \phi + [\sigma][\alpha] \nabla T) = 0$$

④ Obtain the finite element equation by variational principle

$$\begin{bmatrix} K^T & 0 \\ K^{T\phi} & K^\phi \end{bmatrix} \begin{Bmatrix} T_e \\ \phi_e \end{Bmatrix} = \begin{Bmatrix} Q^L \\ I^L \end{Bmatrix}$$



# Three-dimensional Numerical modeling

## Input parameters

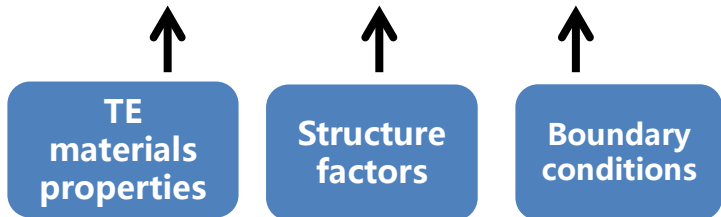
Software interface

A	B	C	D	E	F
Na...	P153 - Resist...	P161 - Tc Magn...	P165 - XYP... .H2	P168 - XYP... .H1	P169 - Thermal Conductivity
Units	ohm m	C	mm	mm	W m <sup>-1</sup> C <sup>-1</sup>
DP 0 (Current)	5.1086E-08	23.83	3.2	5.2	0.1
DP 1	2E-07	20	1	2	0.01
DP 2	4E-07	30	2	4	0.02
DP 3	6E-07	40	3	6	0.03
DP 4	8E-07	50	4	8	0.04
DP 5	1E-06	60	5	10	0.05



## Output performance

G	H	I	J	K	L
P117 - Current Current	P119 - Qh Heat	P120 - Qc Heat	P122 - cold for NBT Temperat...	P123 - cold for P BT Tempe...	P133 - Voltage Probe Electric Voltage
A	W	W	K	K	V
⚡ 6.9516	⚡ 7.4122	⚡ -6.6854	⚡ 323.26	⚡ 315.21	⚡ 0.1046
⚡ 2.4498	⚡ 6.4414	⚡ -6.0873	⚡ 320.96	⚡ 313.59	⚡ 0.14425
⚡ 1.3098	⚡ 6.1613	⚡ -5.9604	⚡ 320.46	⚡ 313.25	⚡ 0.15424
⚡ 0.89391	⚡ 6.0576	⚡ -5.9177	⚡ 320.29	⚡ 313.14	⚡ 0.15789
⚡ 0.67848	⚡ 6.0033	⚡ -5.8961	⚡ 320.2	⚡ 313.08	⚡ 0.15978
⚡ 0.54672	⚡ 5.9698	⚡ -5.8831	⚡ 320.15	⚡ 313.05	⚡ 0.16094

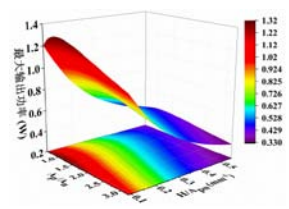


$\sigma$   
 $\kappa$   
 $S$

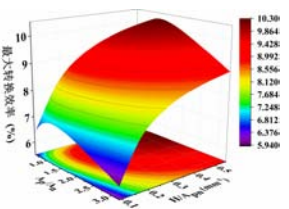
- $H$
- $L_n$
- $L_p$
- $W_n$
- $W_p$
- Gap
- .....

- $T_h$
- $T_c$
- $R_{load}$
- $\rho_{interface}$
- $W_{contact}$
- Convection
- Radiation ...

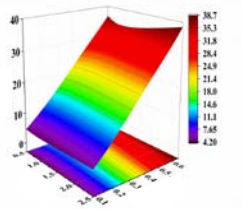
P vs. Structure



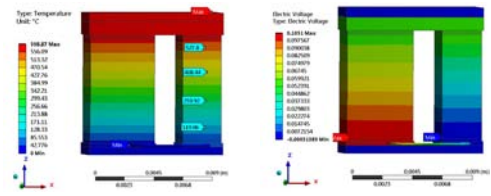
$\eta$  vs. Structure



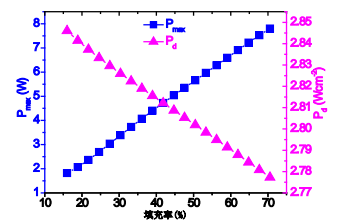
Rin vs. structure



Temp. distribution Voltage distribution

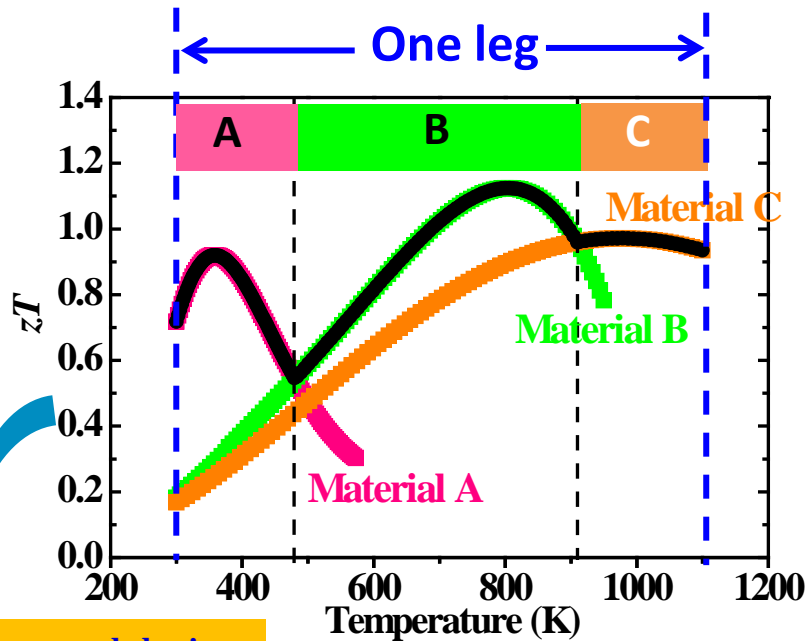


P/PD vs. filling fraction



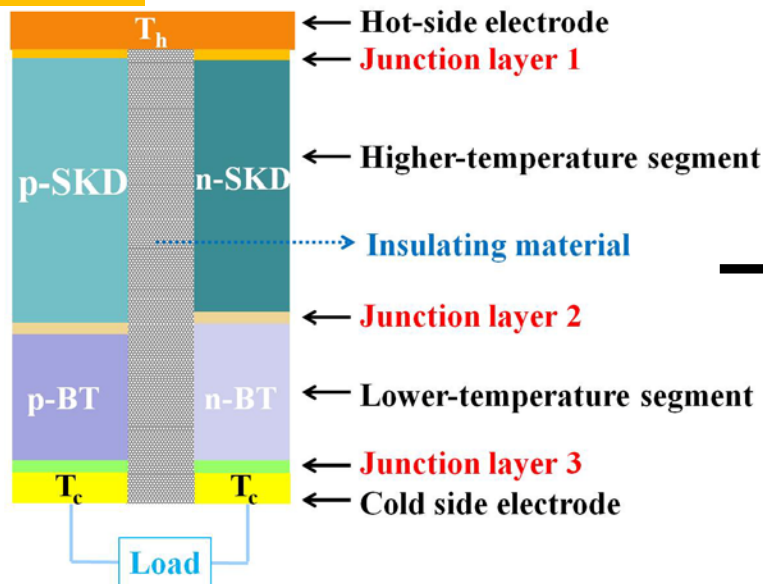
✓ Relationship of "Performance – Structure" could be found out

# Segment: A strategy to realize high efficiency



$$\eta_{\max} = \frac{T_H - T_C}{T_H} \frac{\sqrt{1 + zT} - 1}{\sqrt{1 + zT} + T_C / T_H}$$

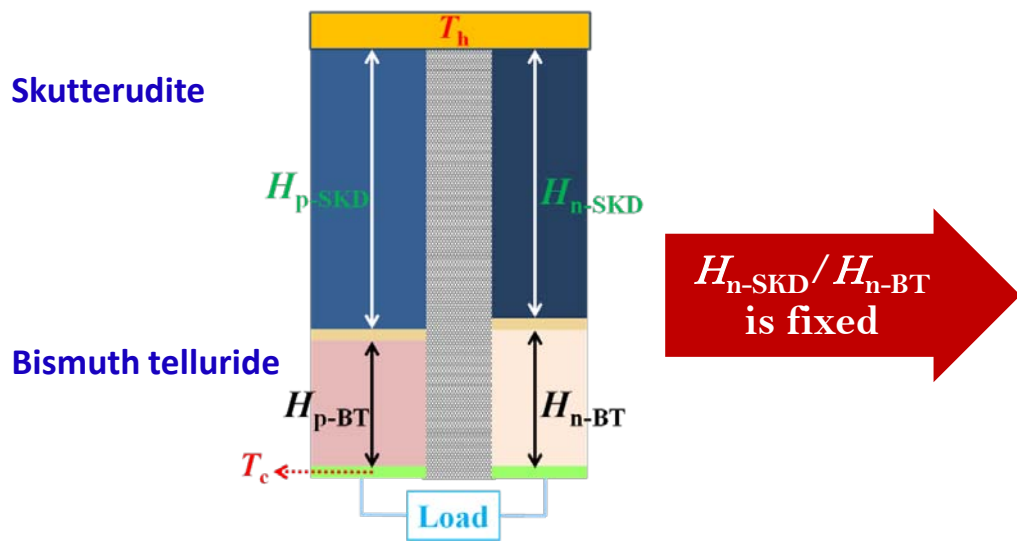
- ◆ A single TE material shows peak  $zT$  under certain temperature range;
- ◆ To build segmented TE device can make each material operate in the temperature range where its efficiency is maximized;
- ◆ Enhance  $zT$  &  $\Delta T$  simultaneously.



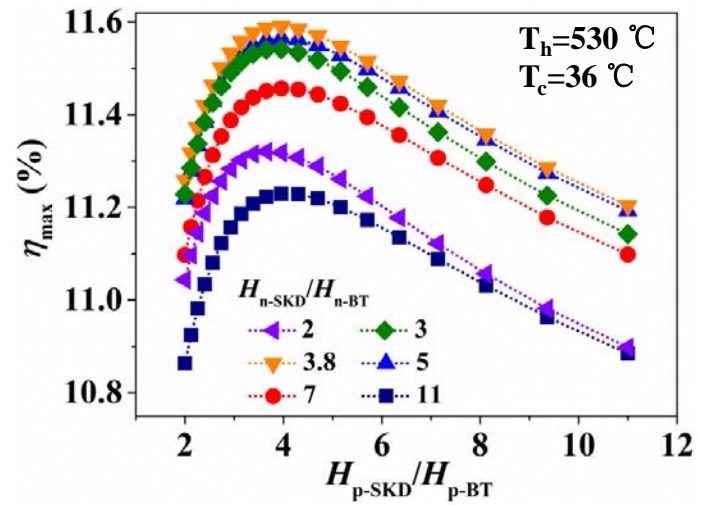
Increased interfaces lead to more energy losses

Complex structure brings more difficulty for topological design

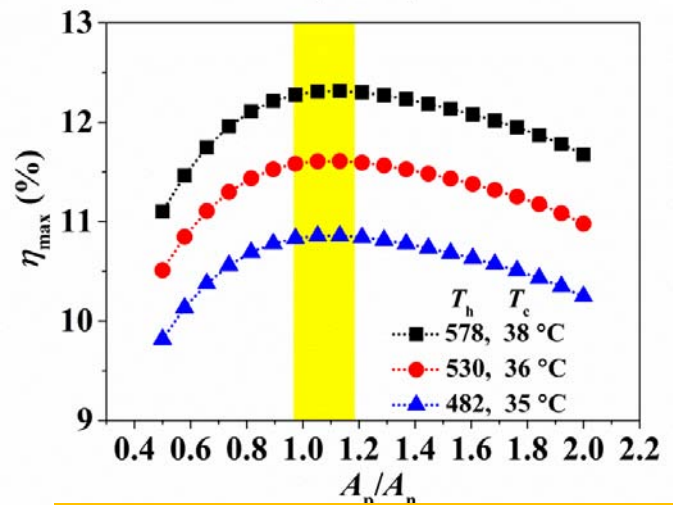
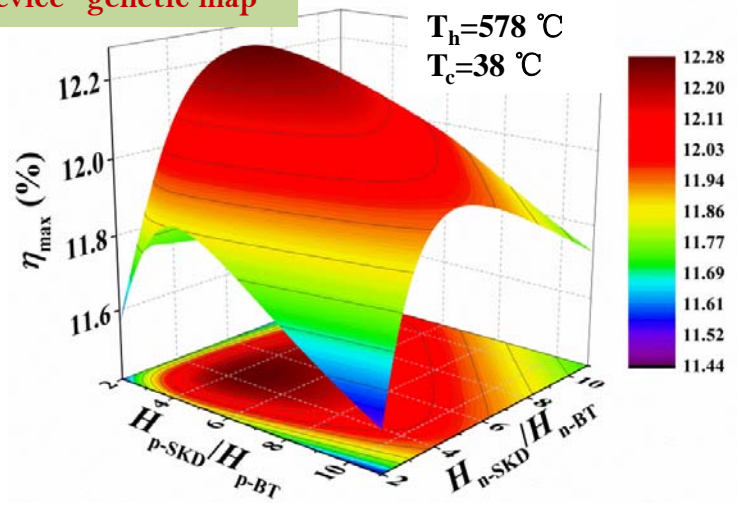
# Leg geometry optimization of segmented module



*p*- and *n*-type legs are mutually constrained due to the reallocation of the heat flow.



TE device "genetic map"



Synchronously optimize two legs for optimum ratio

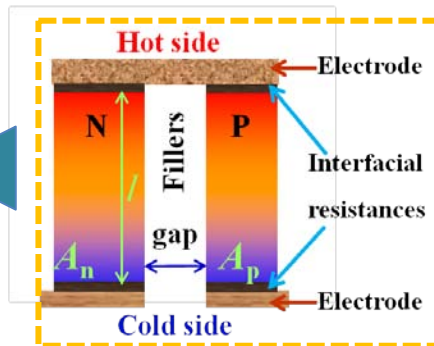
Optimize cross-sectional area ratio

# Multi-parameter optimization of segmented module

## Thermal loss analysis

Additional boundary conditions:  
gap,  $\kappa_F$

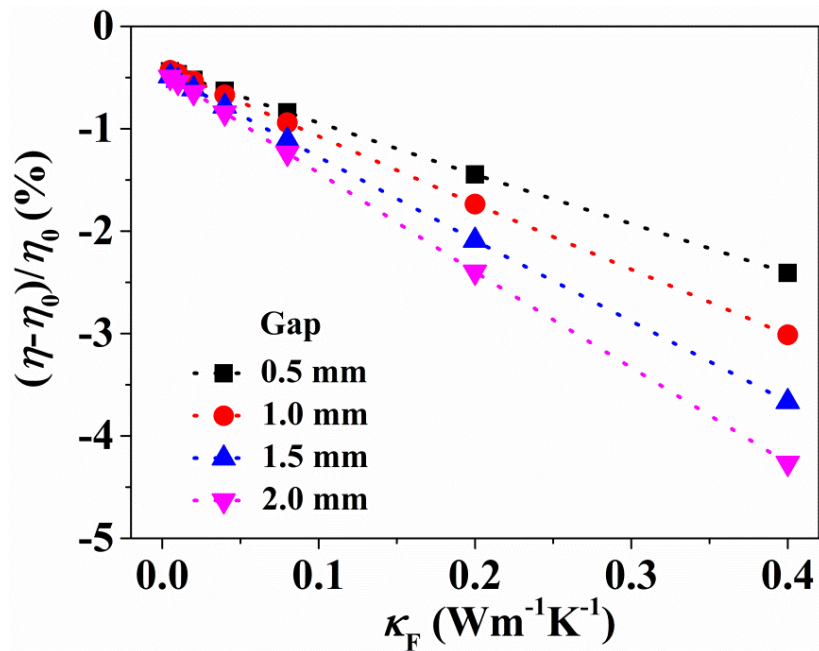
Plot :  
 $\eta(T)$  vs gap &  $\kappa_F$



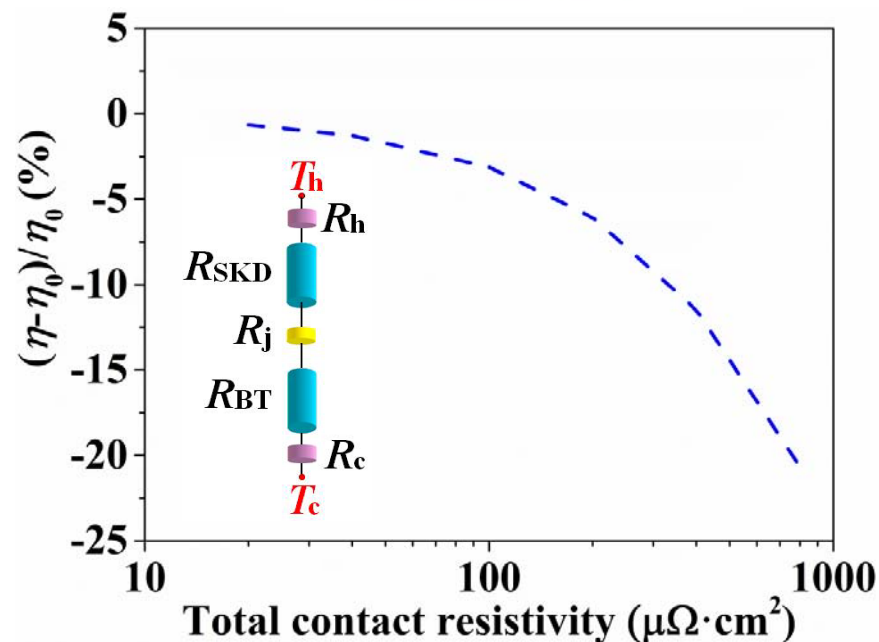
## Electrical loss analysis

Additional boundary conditions:  
 $\rho_c$

Plot :  
 $\eta(T)$  vs  $\rho_c$



➤ Efficiency loss increases with the increasing thermal conductivity of fillers & gap distance

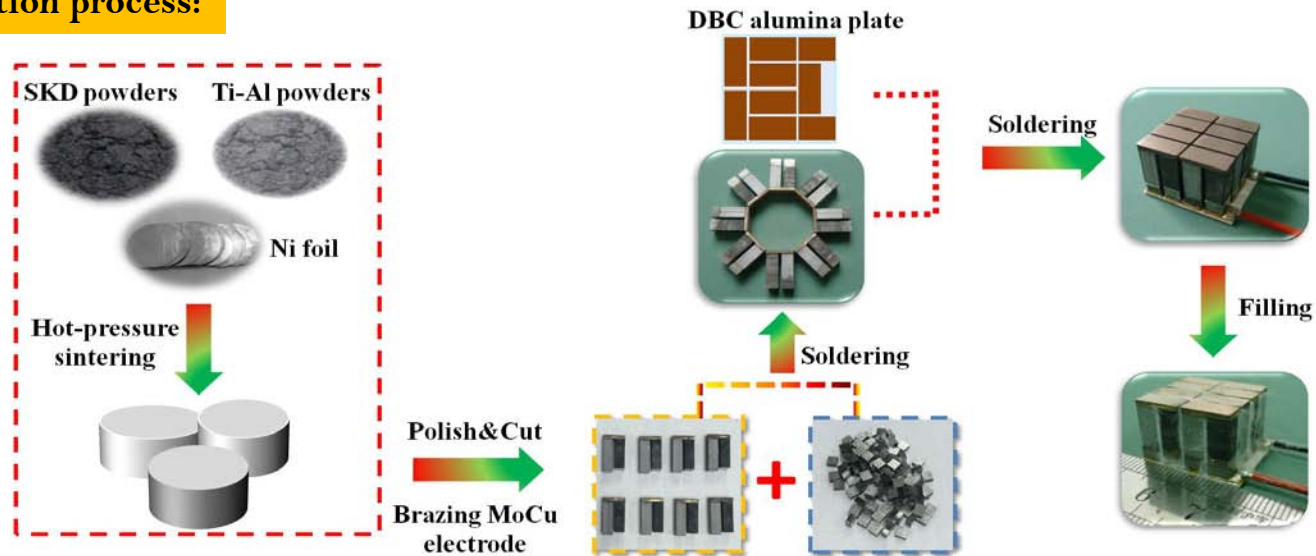


➤ The increased total  $\rho_c$  leads to more losses in the efficiency

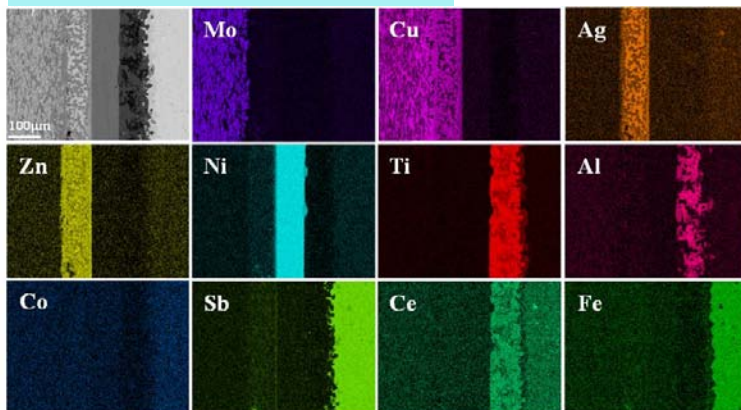


# Segmented BT/SKD module integration

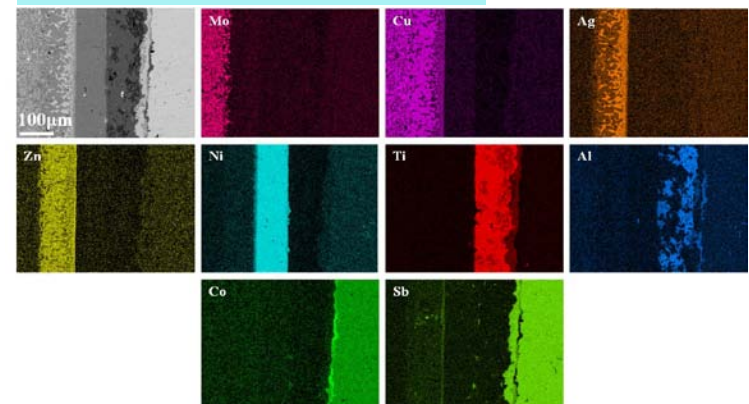
## Overall fabrication process:



## p-SKD/MoCu junction

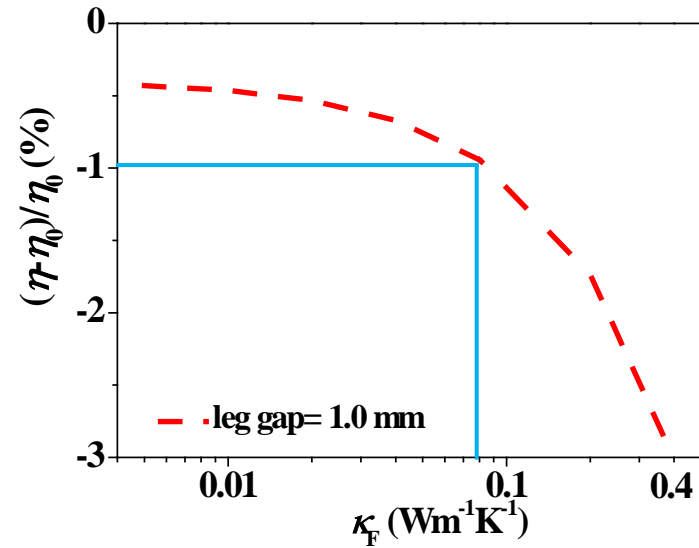
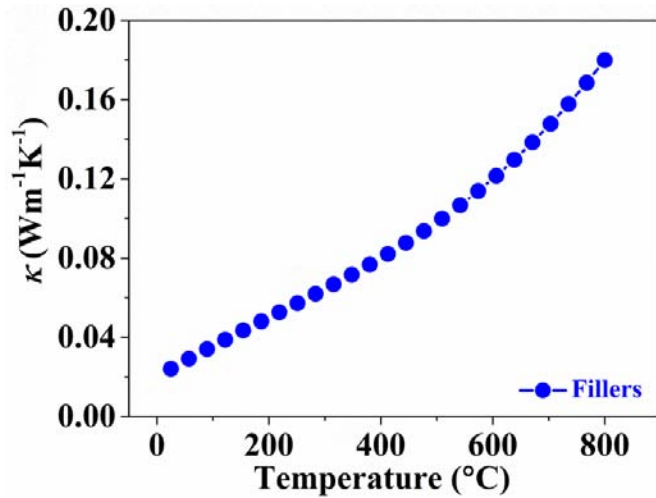


## n-SKD/MoCu junction

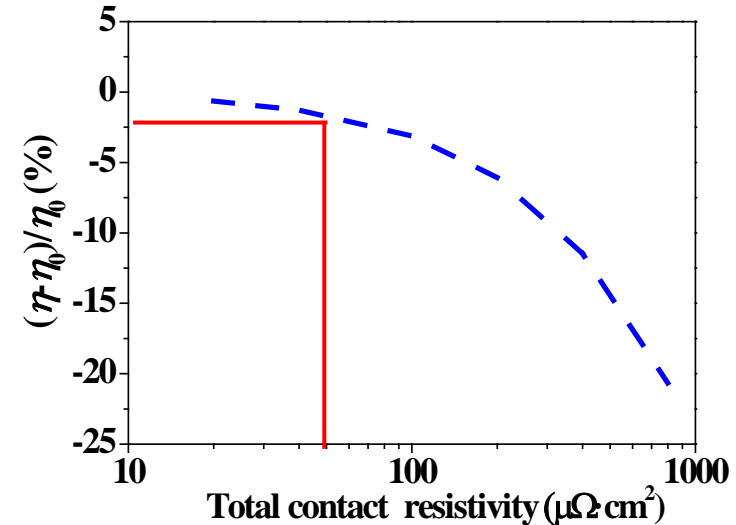
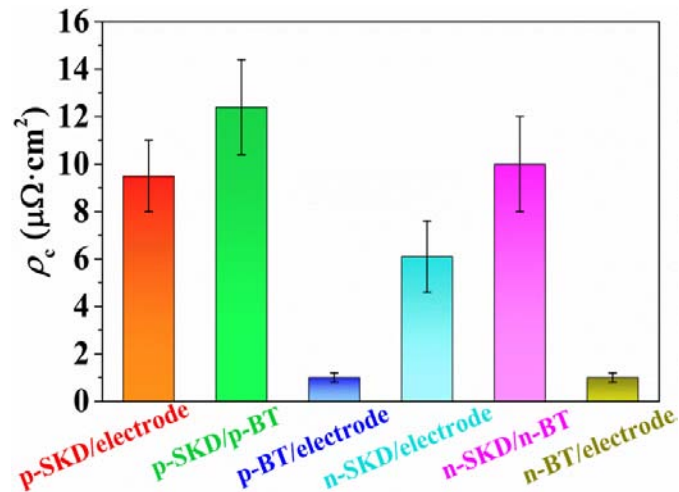


Microstructure and composition shows excellent interface bonding, no crack & no diffusion

# Energy loss characterization



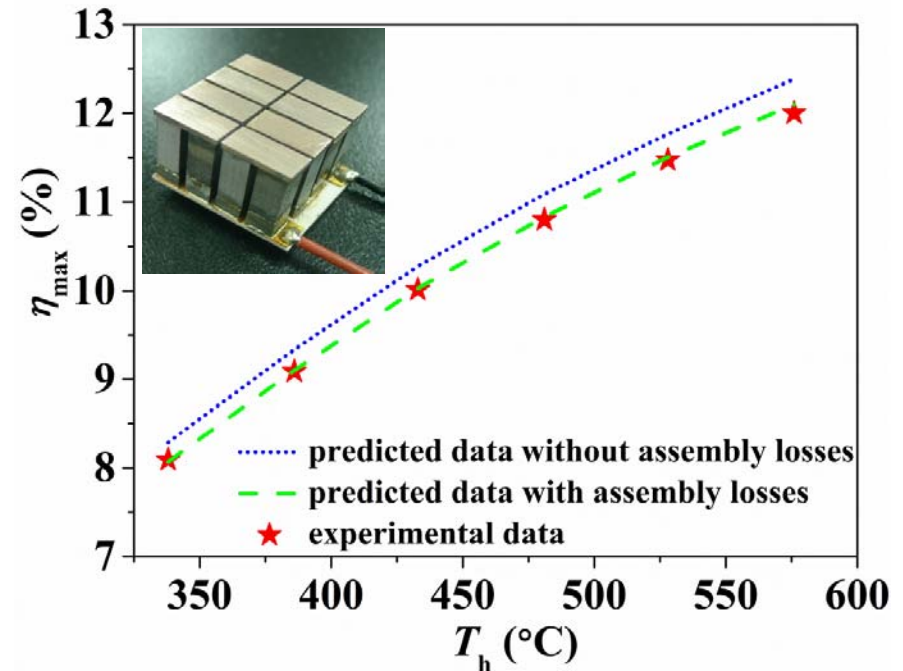
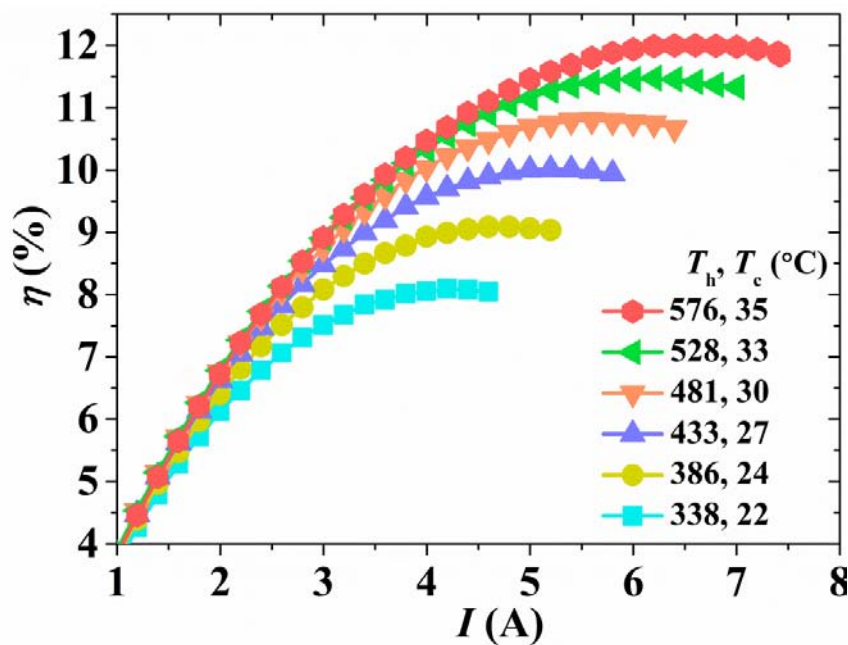
➤ Glass fibers with the average  $\kappa$  of **0.09**  $\text{Wm}^{-1}\text{K}^{-1}$  cause a merely 1 % reduction in  $\eta_{\max}$



➤ Composition of each interface was optimized.  $\rho_c \sim 40 \mu\Omega \cdot \text{cm}^2$  causes <2% loss in  $\eta_{\max}$

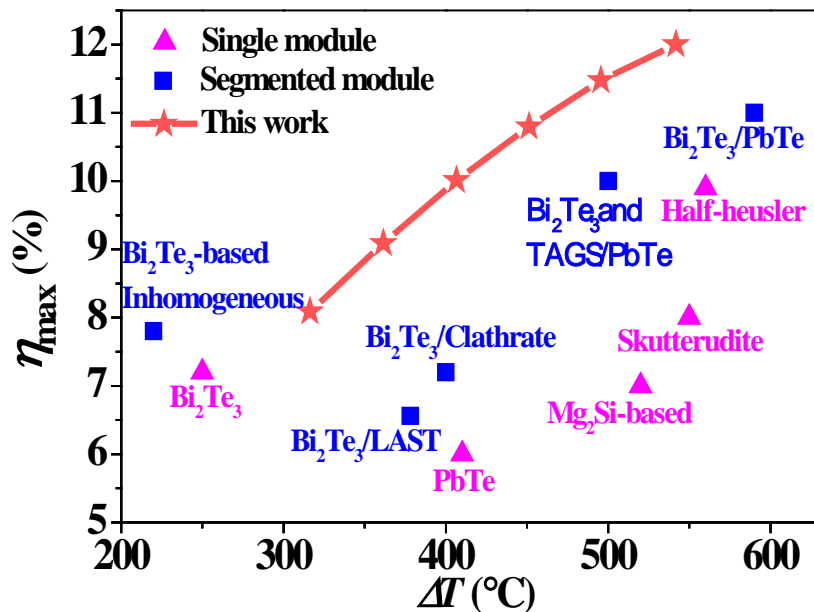
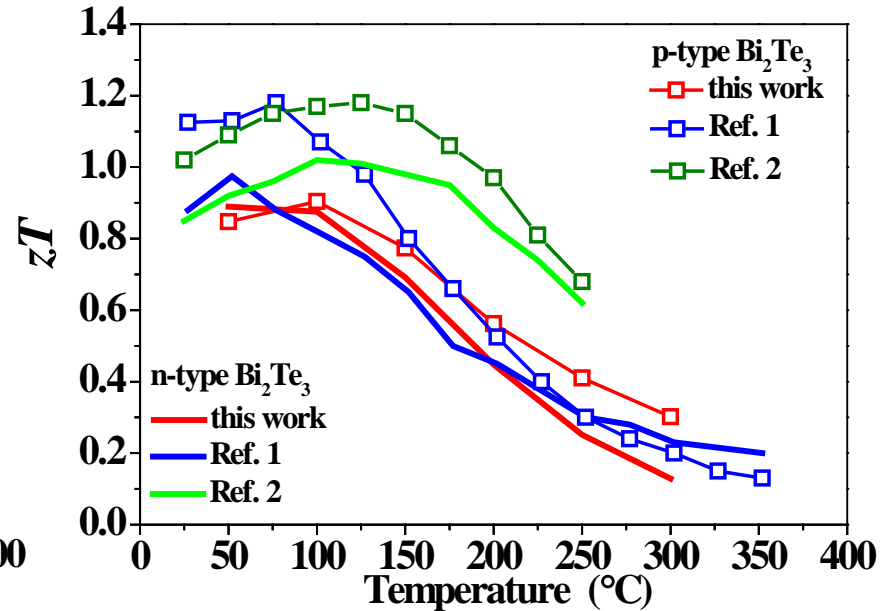
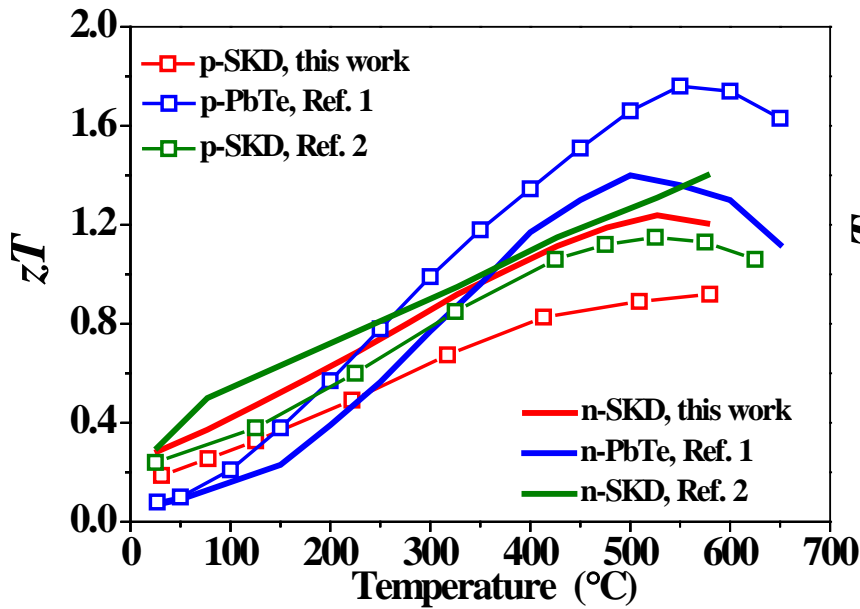
# Characterization of the segmented BT/SKD module

## Thermoelectric conversion efficiency:



- $\Delta T = 316$  °C,  $\eta_{\max} = 8\%$ ;  $\Delta T = 541$  °C,  $\eta_{\max} = 12\%$ ;
- Experimental data agree well with the simulated results;
- $\eta_{\max}$  reaches  $\sim 97\%$  of the ideal efficiency based on the TE materials themselves.

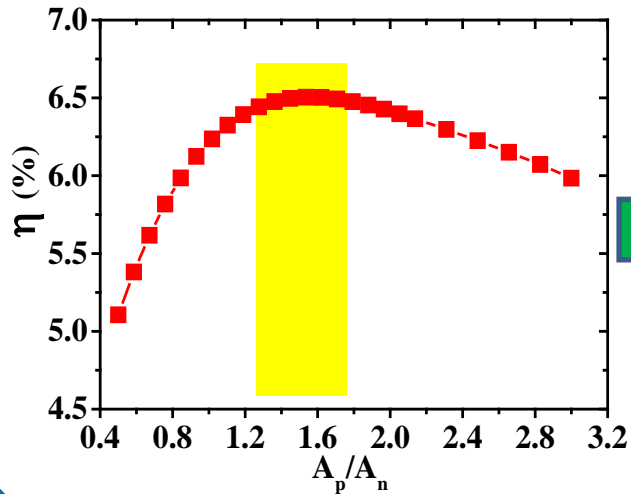
# Comparison with the literatures



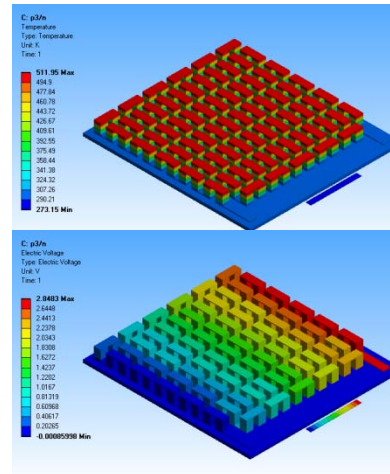
➤ Using **Low  $zT$**  value TE materials (scaling up fabricated or commercial) can achieve a **high  $\eta_{\text{max}}$**  TE modules, due to the rational structure design and minimum energy losses.

# Topologic design application: single-stage BT module

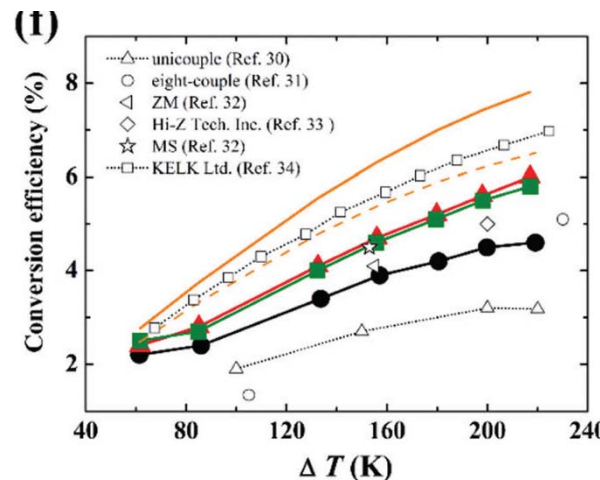
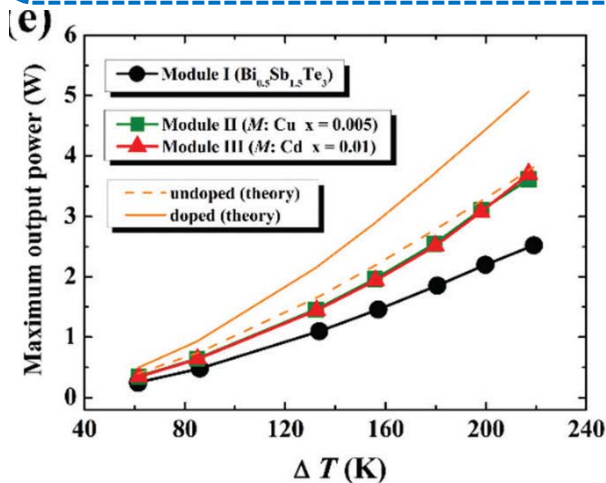
## Structure optimize



## Performance simulation



## Module integration



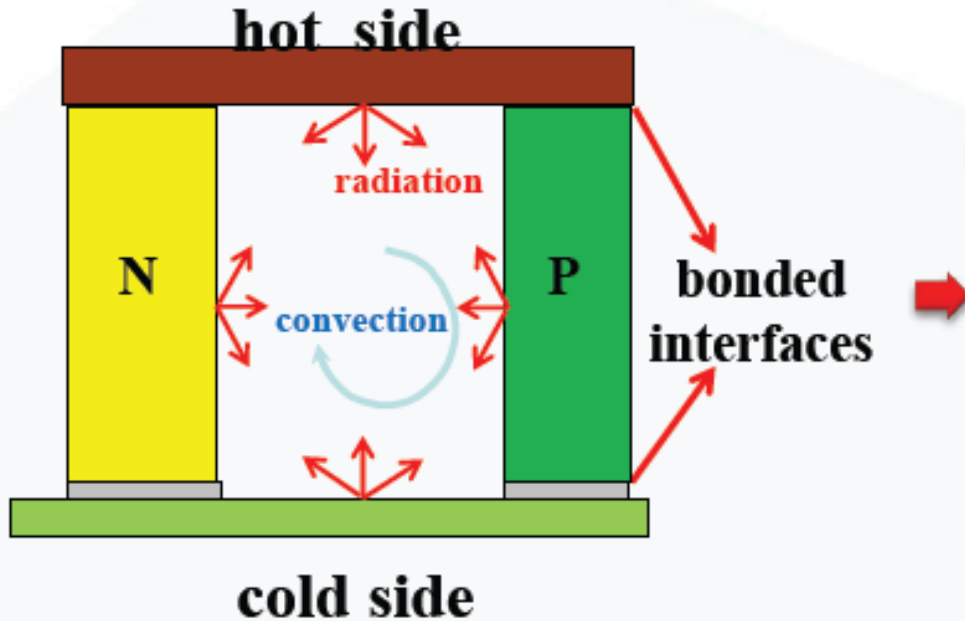
Combining the high  $ZT$  p-type  $\text{Bi}_2\text{Te}_3$ -based materials and optimal structure, the module's efficiency reached **6.0% @  $\Delta T = 217$  K**, which superior to commercial modules.

Thanks to *Dr. Hsu-Shen Chu* from ITRI for module integration.

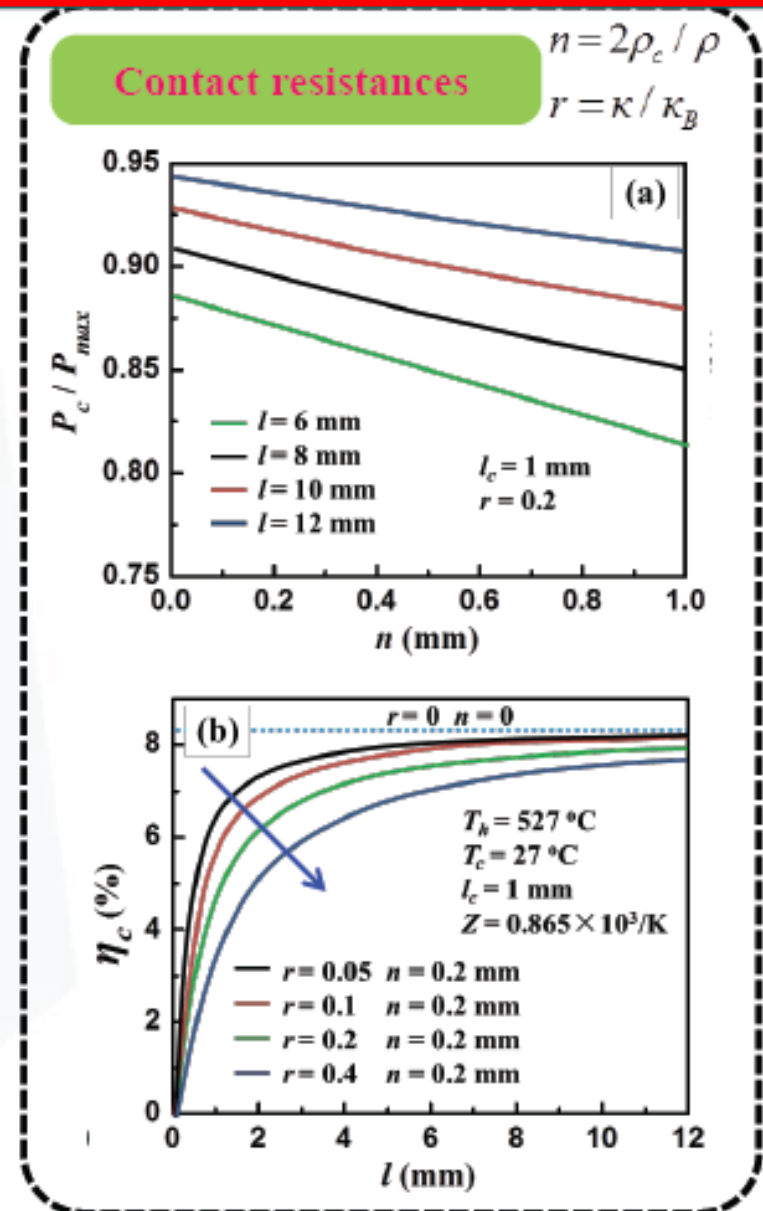


# Device assembly factor: Energy loss

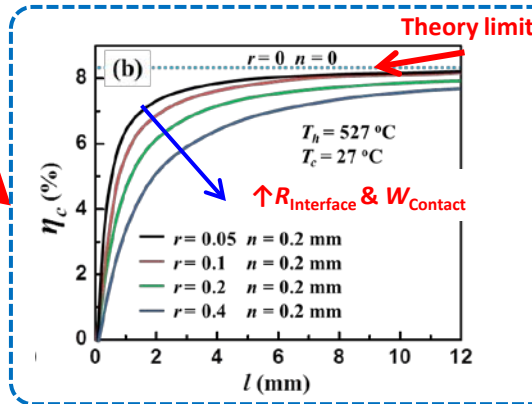
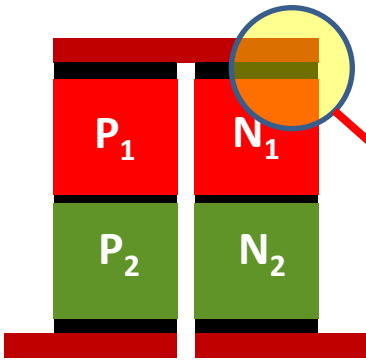
Device assembly loss: electrical & thermal



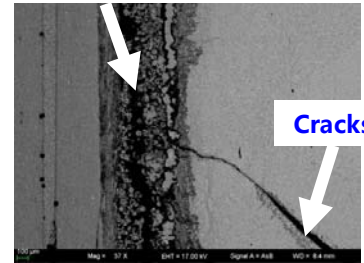
- ◆ Electrical and thermal resistances at various interfaces
- ◆ Thermal radiation and/or convection through the element gaps
- The actual output performances below the theoretical values



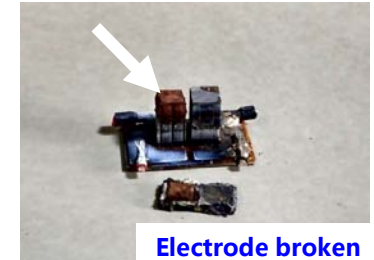
# Interface : Key issue of high efficiency & high reliability



Interfacial diffusion



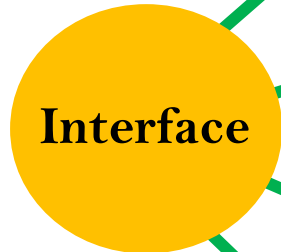
Oxidation



SKD module : 500°C×10 days in air

## Working Conditions:

- High Temp.
- Large Temp. Diff.
- Oxide & humidity
- Corrosively
- Thermal shock
- Vibration



## Electrical

- ✓ High electrical conductivity
- ✓ Low interfacial resistivity

## Thermal

- ✓ High thermal conductivity
- ✓ Low contact resistivity

## Mechanical

- ✓ Good bonding strength
- ✓ Minimize residual stress

## Chemical

- ✓ Stable at high temperature
- ✓ Block interfacial diffusion

- ◆ Complex working conditions caused a complex interface behavior.
- ◆ Most of structural and functional failures of TE modules are caused by the evolution of the interfaces.
- ◆ A high reliable interface with minimized energy loss is the key issue to realize a TE module with both high efficiency and high reliability.

# Interfacial physical properties: Influent performance

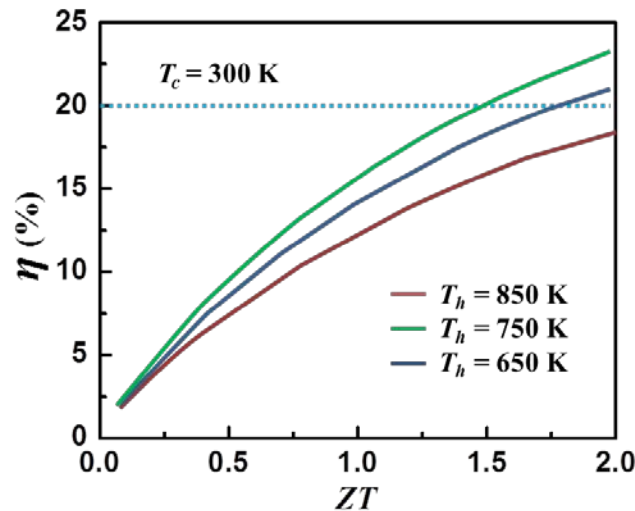
## Output power & efficiency:

$$P = \frac{S^2(T_h - T_c)^2}{4R} \cdot \frac{1}{(1+n/l)(1+2rv)^2}$$

$$\eta = \frac{T_h - T_c}{T_h} \left\{ (1+2rv)^2 \left[ 2 - \frac{1}{2} \left( \frac{T_h - T_c}{T_h} \right) + \frac{4}{ZT_h} \left( \frac{1+n/l}{1+2rv} \right) \right] \right\}^{-1}$$

### Efficiency vs. $ZT$

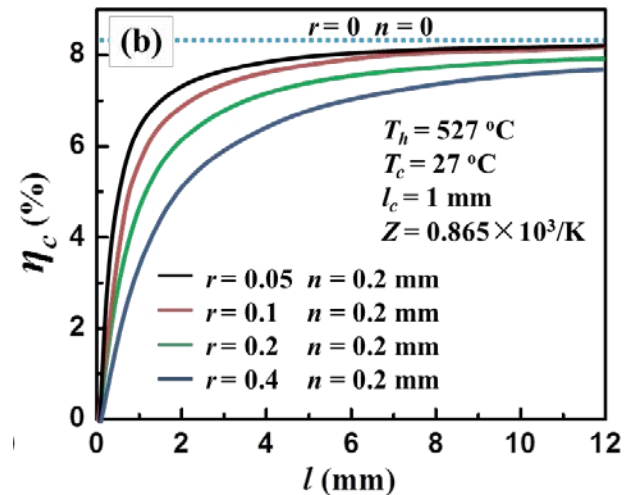
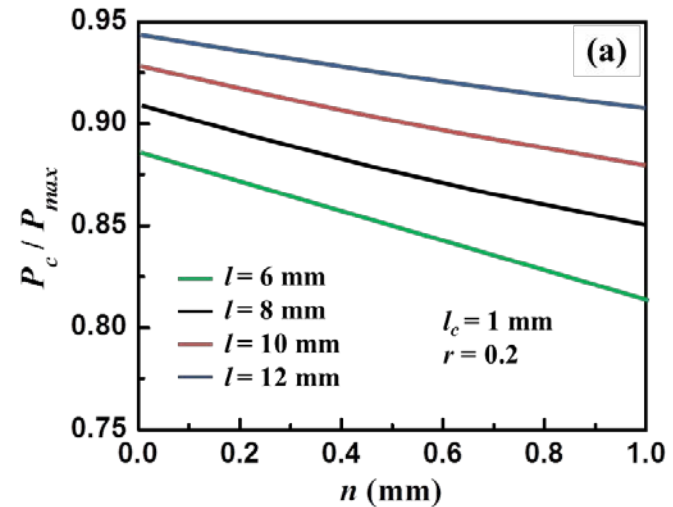
$$ZT = \frac{S^2 \sigma}{\kappa} T$$



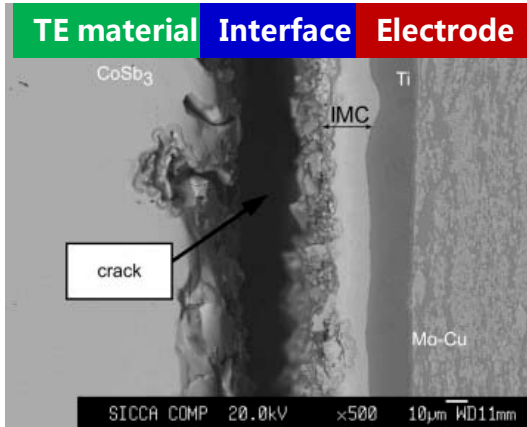
### Interface influence

$$n = 2\rho_c / \rho$$

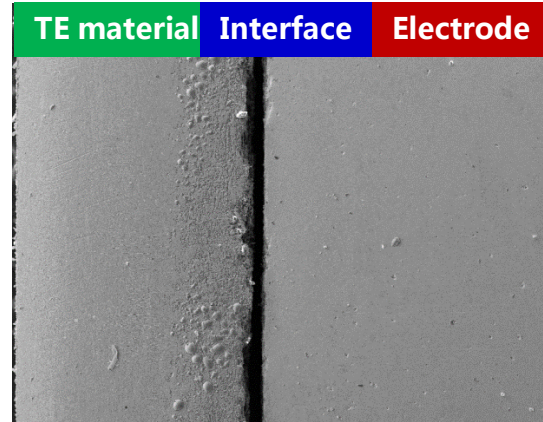
$$r = \kappa / \kappa_B$$



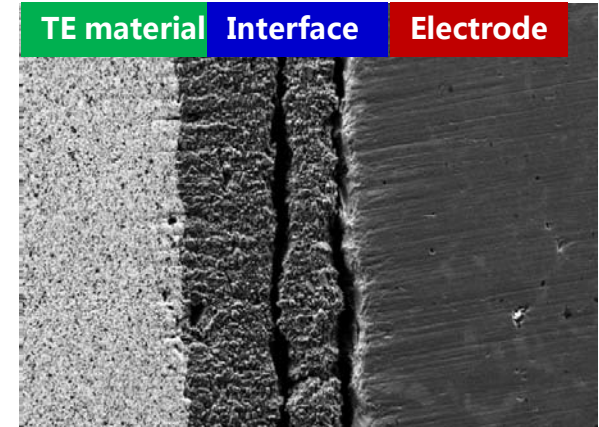
# Interfacial chemical properties: Influent reliability



**Skutterudite module**  
Failure position : IMC



**Half-Huesler module**  
Failure position : IMC



**SiGe module**  
Failure position : IMC

## Structural failure:

- ◆ **Position:** Interface of intermetallic compounds.
- ◆ **Reasons:** Interfacial diffusion, chemical reaction, oxidation, sublimate, .....

Interface design must combining contact properties (strength, conductivity) & diffusion barrier.

# Principle of choosing diffusion barrier(buffer) layer

## Qualitative principle:

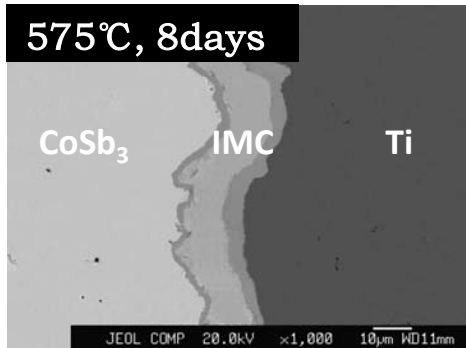
- Chemical : Reaction possible → Improve the bonding strength improvement  
Low diffusion speed → Improve the interface reliability
- Thermal & electrical :  $10^1 \sim 10^2$  higher than TE materials → Reduce energy loss
- CTE: close to TE materials → Reduce the stress
- Others: Melting point  $\gg$  Working temperature

Candidate	Diffusion properties	MP/°C	$\sigma$ ( $10^6$ S/m)	$\kappa$ ( W/cm.K )	CTE (ppm)	
Matrix	<b>SKD</b>	873	0.06~0.2	0.02~0.03	9~11	
Buffer layer	Ti	?	1700	2.4	2.2	8.4
	Zr	?	1852	2.4	2.3	5.8
	Hf	?	2227	2.8	2.3	5.9
	Nb	?	2467	8	5.4	7.1
	Ta	?	3014	8	5.8	6.6
	Cr	?	1857	7.9	9.4	6.2
	Mo	?	2617	19	13.8	5.4

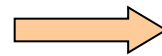
\*Interfacial diffusion properties must be obtained by experiment.



# Degradation mechanism: Inter-diffusion at interface

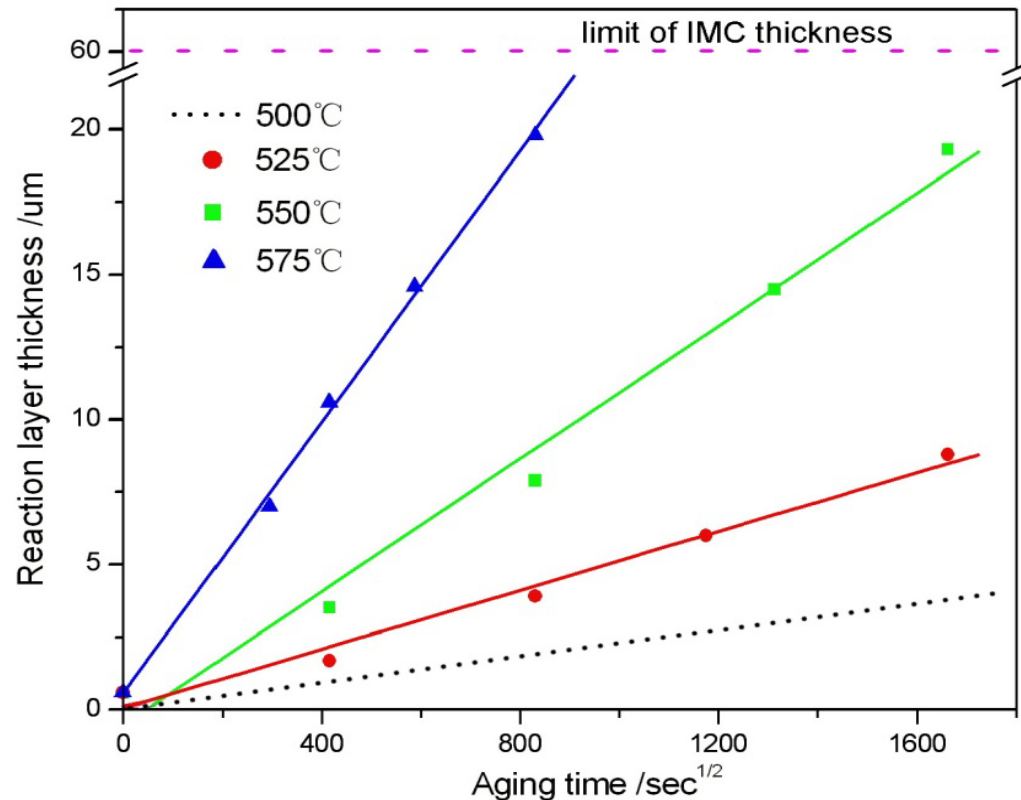
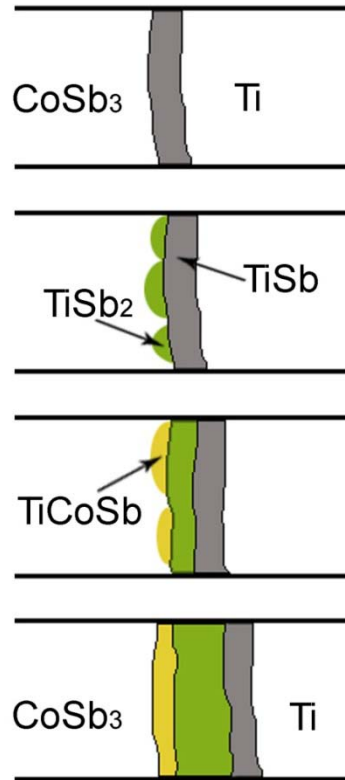


CoSb<sub>3</sub>/TiSb/Ti

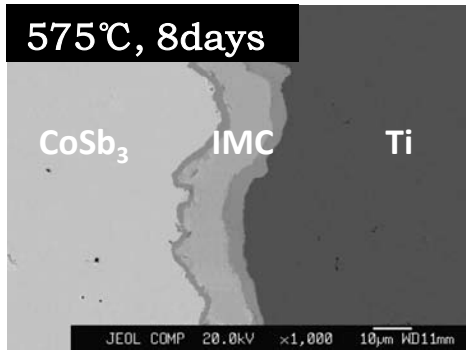


CoSb<sub>3</sub>/TiCoSb/TiSb<sub>2</sub>/TiSb/Ti

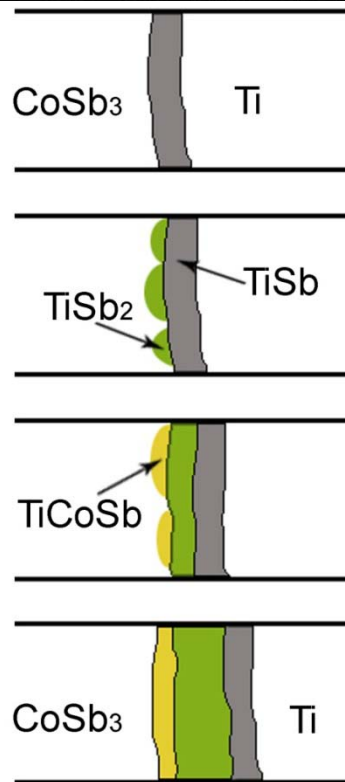
The interfacial microstructure evolution is mainly caused by the Sb diffusion to form intermetallic compound layer and this layer causes the degradation and final destruction.



# Optimization of interface microstructure



The high activity of Ti interlayer benefits the sintering/bonding between SKD and MoCu electrode, but also causes the degradation due to the inter-diffusion at high temperature.



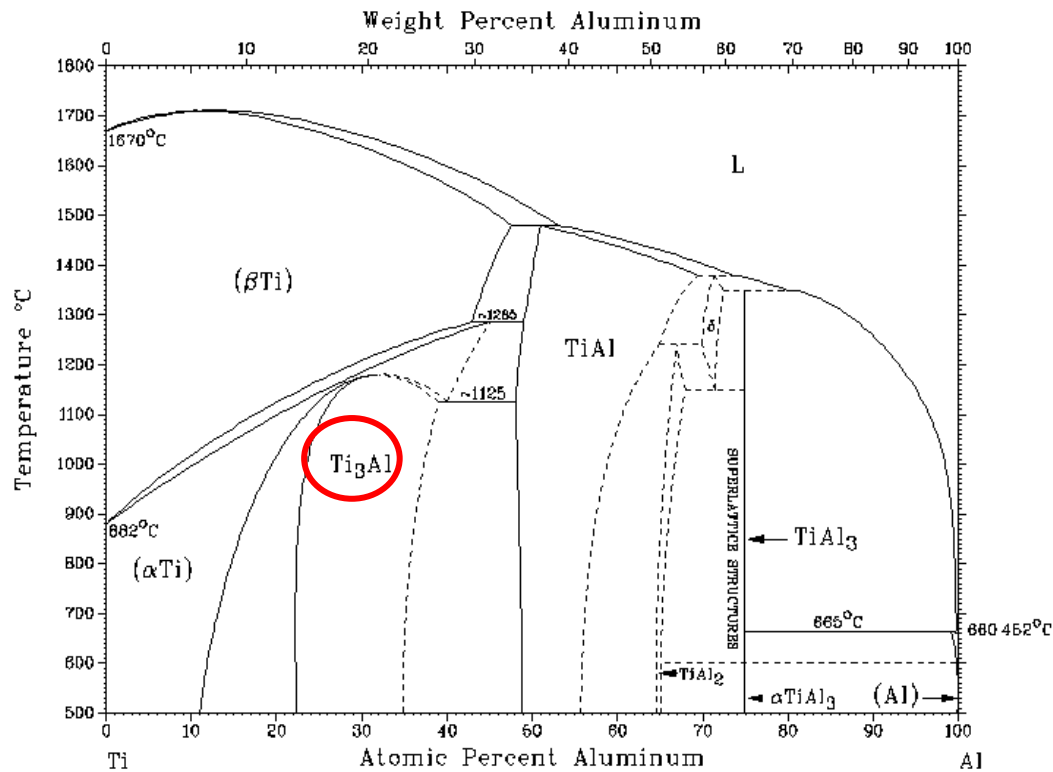
**Optimization of interfacial microstructure and bonding technique:**

Keep low interfacial R (T&E) → **efficiency**

Depress high-T inter-diffusion → **reliability**

*Tune high temperature activity (diffusion and reaction) of interlayer: find new Ti-based alloy as interlayer instead of Ti.*

# Ti-Al alloy: Balance high-T stability & bonding activity

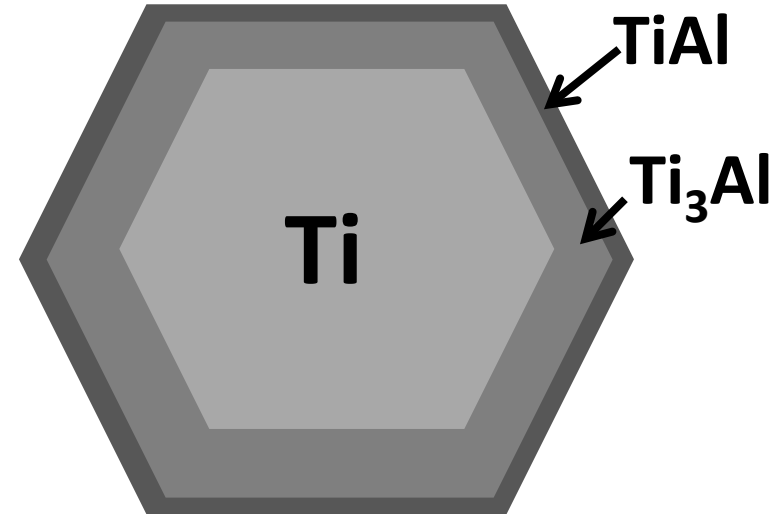
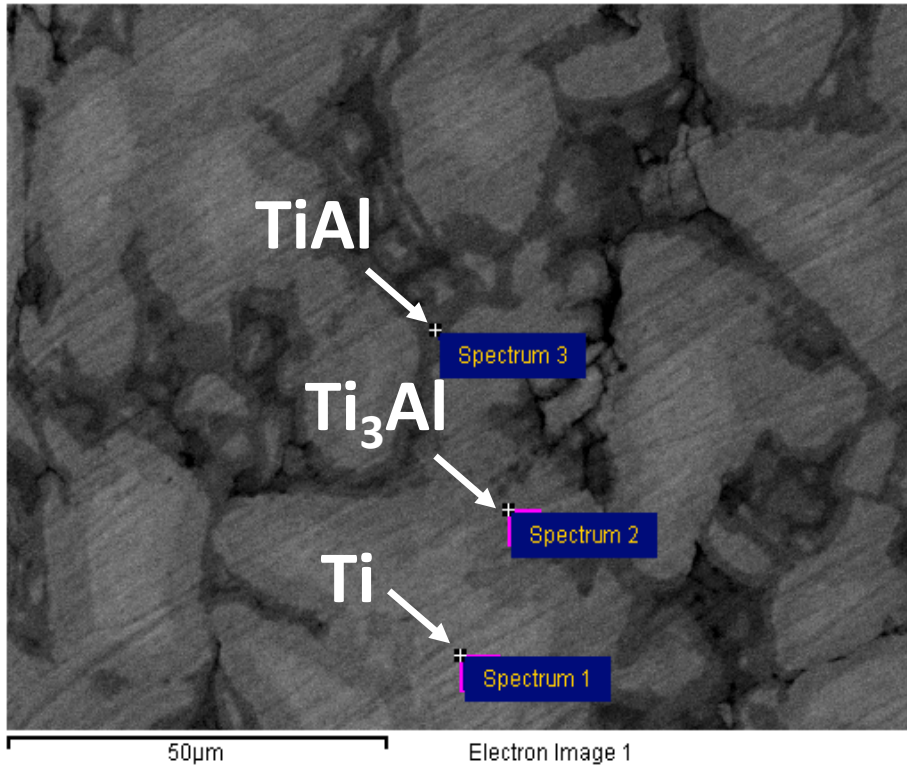


In Ti-Al binary system, there exist several electrically conductive compounds with high-T stability, which are known easily form by solid state reaction.

- ◆ Maintain high reaction activity during sintering.
- ◆ Suppress activity after sintering or during high-T service due to the formation of stable  $Ti_xAl$ .
- ◆ The  $Ti_xAl$  layer should not raise interfacial thermal/electrical resistance, while maintaining good bonding strength.

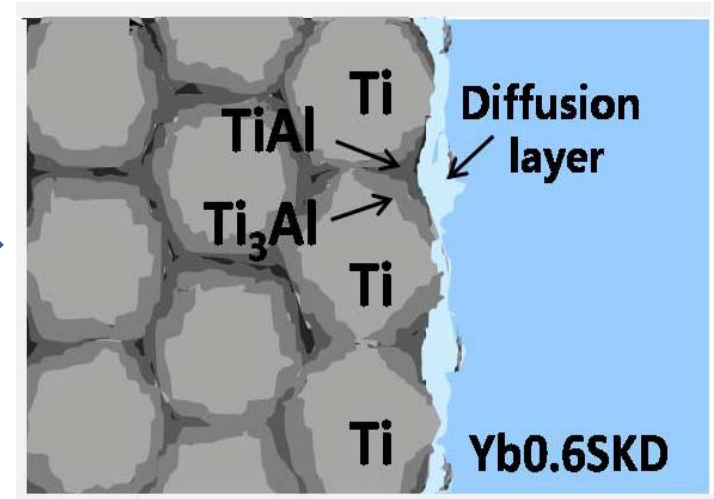
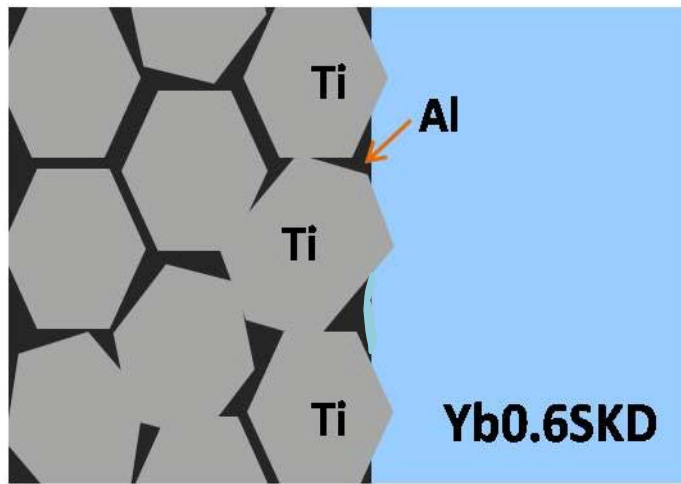
# Microstructure of Ti-Al interlayer

after annealing at 550°C



***SEM and EPMA indicate the formation of Ti<sub>3</sub>Al and TiAl alloys on the surface of Ti particles during high temperature annealing.***

# Sketch: Formation of Ti/Ti<sub>3</sub>Al “core-shell” structure



**Before sintering:**

MoCu / (Ti+Al) / SKD

→ Ti & Al metals possess high activity and enable reaction and bonding during sintering.

**After sintering or during high temperature operation:**

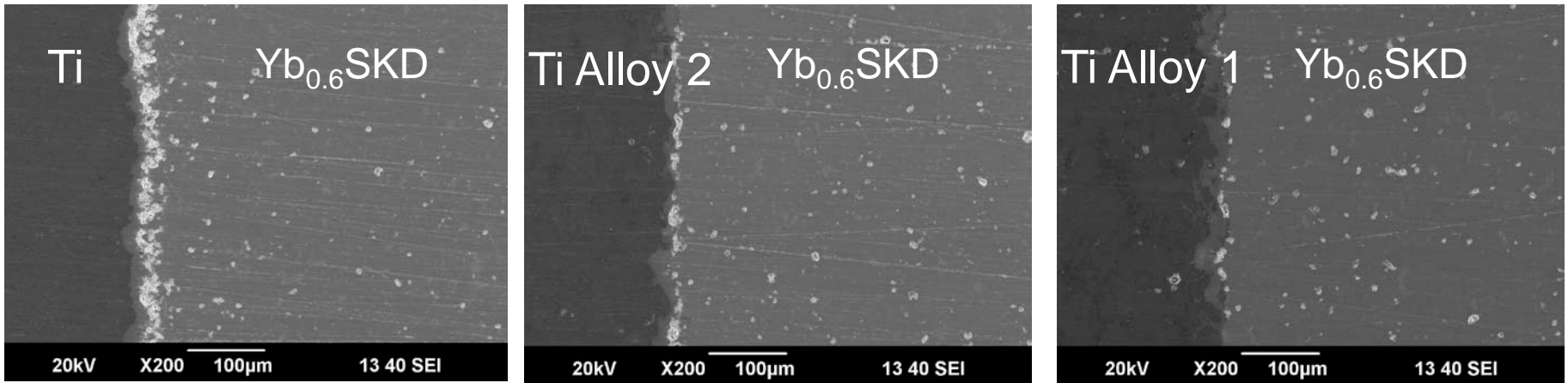
Ti+Al → Ti+Ti<sub>3</sub>Al (or TiAl)

→ Ti/Ti<sub>3</sub>Al core/shell structure prevents further Ti-diffusion and realize high stability.



# Stability of Ti-Al interlayer: Microstructure

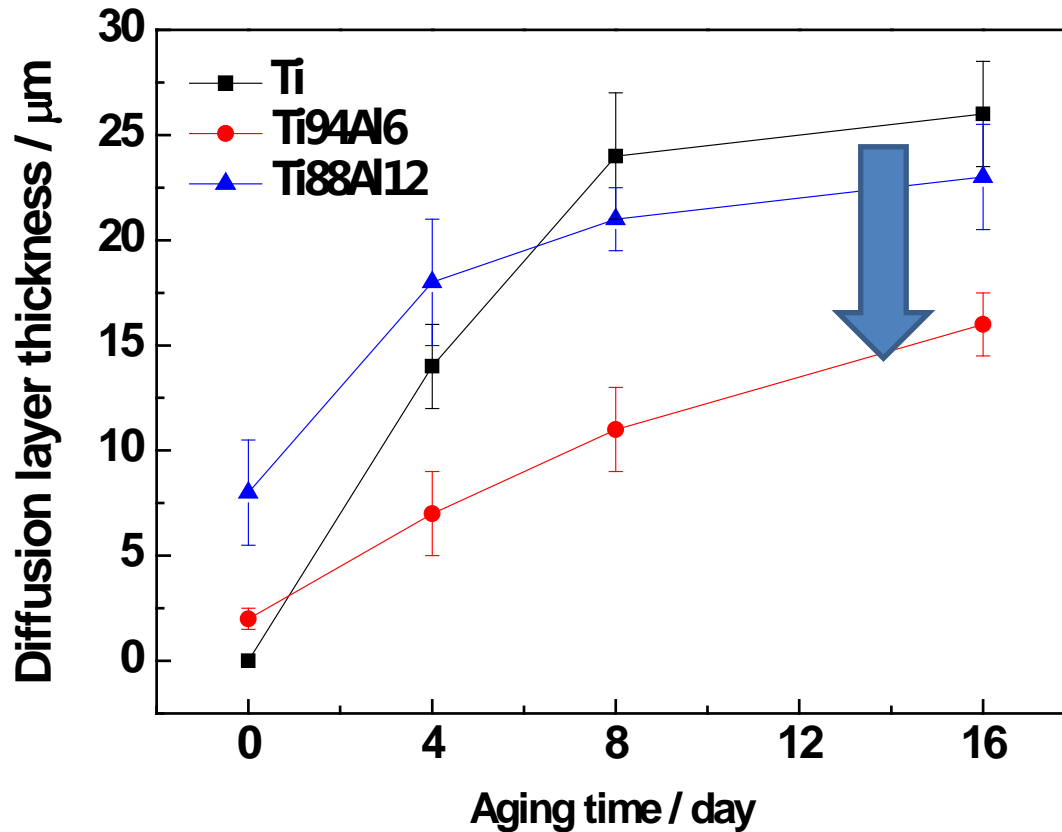
*High temperature stability for different Ti-based alloy interlayers.*



**SEM images of cross section of elements after aging at 600°C for 16 days in vacuum.**

- No (or less) formation of TiCoSb brittle phase on the interface.**
- The formation of TiCoSb intermetallic layer is effectively prevented by Ti<sub>x</sub>Al alloying.**

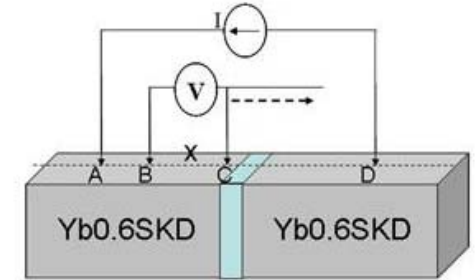
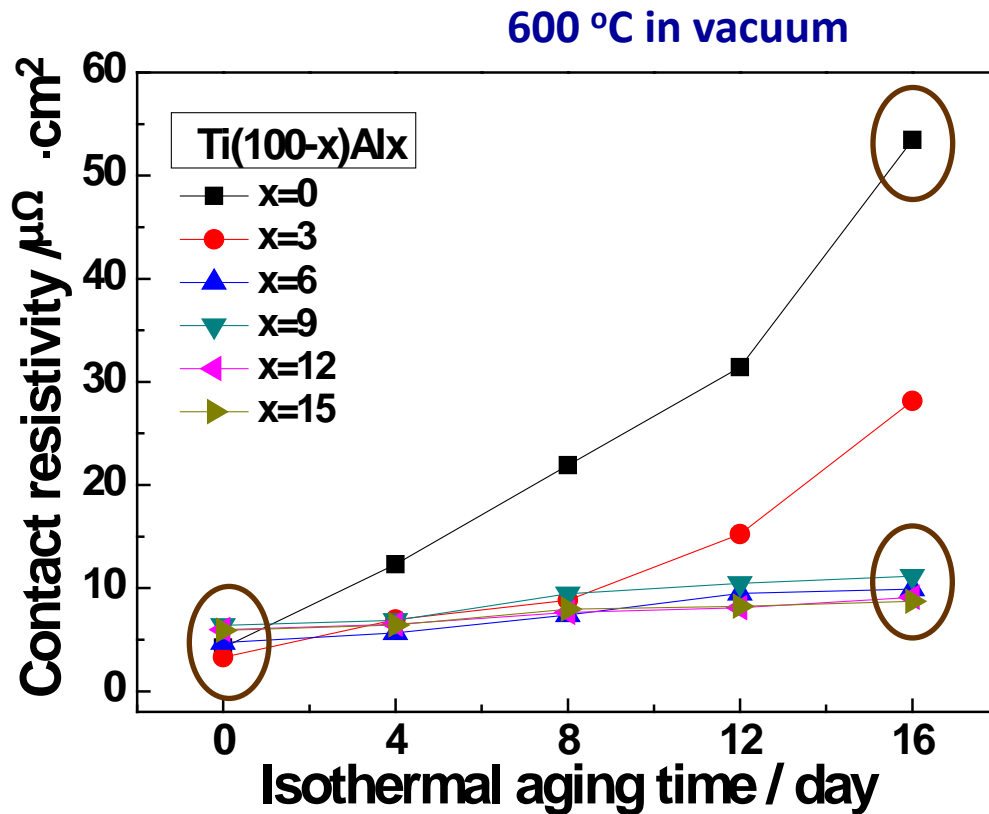
# Stability of Ti-Al interlayer: Diffusion layer



At 600°C in vacuum, 16 days

The growing speed of diffusion layer was greatly decreased after alloying Ti and Al.

# Interfacial resistance of $\text{Ti}_{100-x}\text{Al}_x / \text{Yb}_{0.6}\text{Co}_4\text{Sb}_{12}$ joints



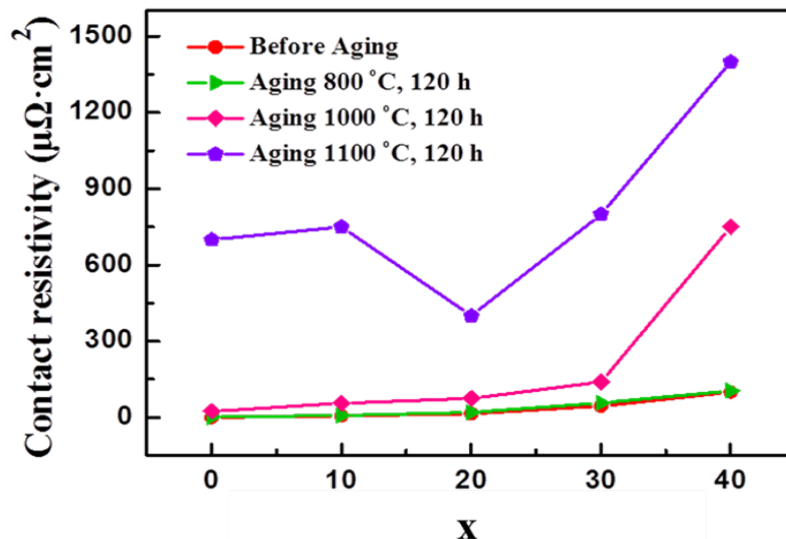
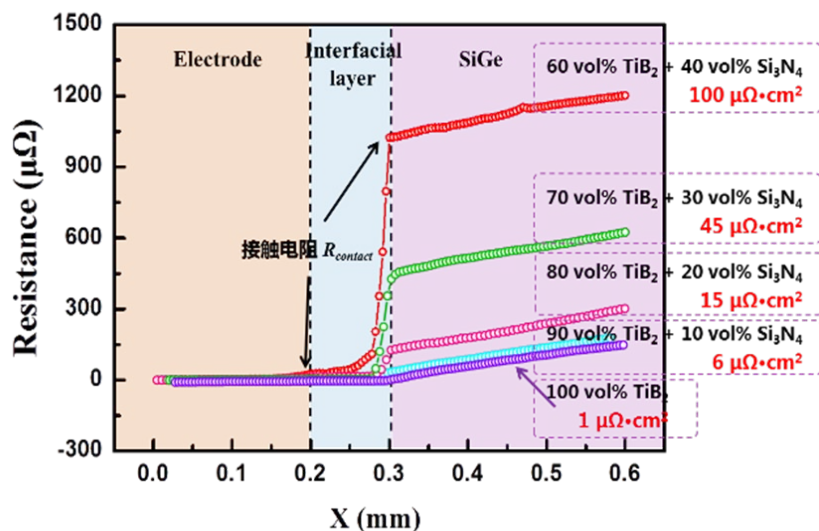
X	$\rho_{c0}$ ( $\mu\Omega \cdot \text{cm}^2$ )	$\rho_{c16}$ ( $\mu\Omega \cdot \text{cm}^2$ )
0	4.2	53
3	3.3	28
6	4.7	10
9	6.4	11
12	6	9
15	5.9	9

- ❑ **Ti interlayer:**  $\rho_c$  increased by 12 times of its initial value after aging.
- ❑ **Ti-Al alloying interlayer:**  $\rho_c$  changed less than twice after aging.

# Interface design target: Low energy loss & high reliability

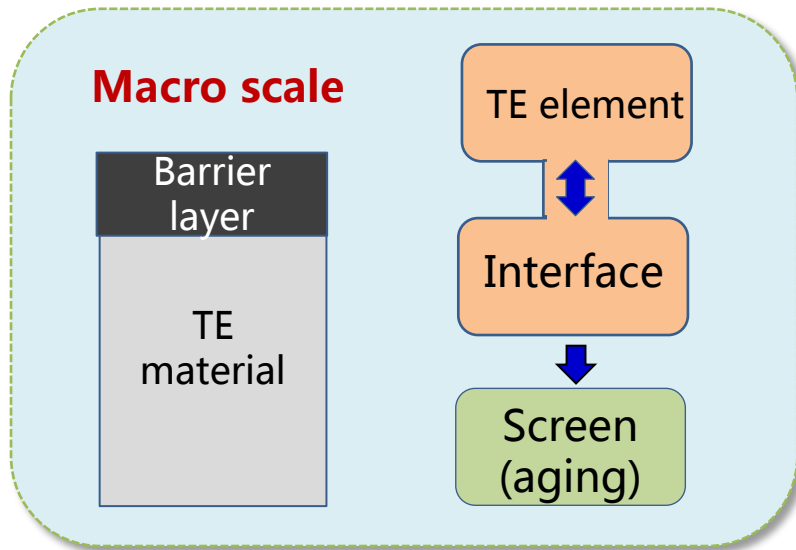
## ◆ SICCAS established interface solutions for several TE materials :

TE materials	Electrode					Barrier layer	$\rho_{inter}$ ( $\mu\Omega\text{cm}^{-2}$ )	$\Delta \eta$
	Content	$\sigma$ (S/m)	$\kappa$ (W/m·K)	CTE ( $10^{-6}\text{K}^{-1}$ )				
				Electrode	TE			
<b>Bi<sub>2</sub>Te<sub>3</sub></b>	AlCu	$3 \times 10^7$	300	20	15~22	Ni-Mo	< 10	< 3%
<b>CoSb<sub>3</sub></b>	MoCu	$2.6 \times 10^7$	98	10.3	9.7~12.8	Ti-Al	< 10	< 3%
<b>Half-heusler</b>	MoCu	$2.6 \times 10^7$	98	10.3	9.8~11.5	Zr-Al	< 5	< 2%
<b>SiGe</b>	W-Si <sub>3</sub> N <sub>4</sub>	$4.4 \times 10^6$	49	4	4	TiB <sub>2</sub> - Si <sub>3</sub> N <sub>4</sub>	< 20	< 5%

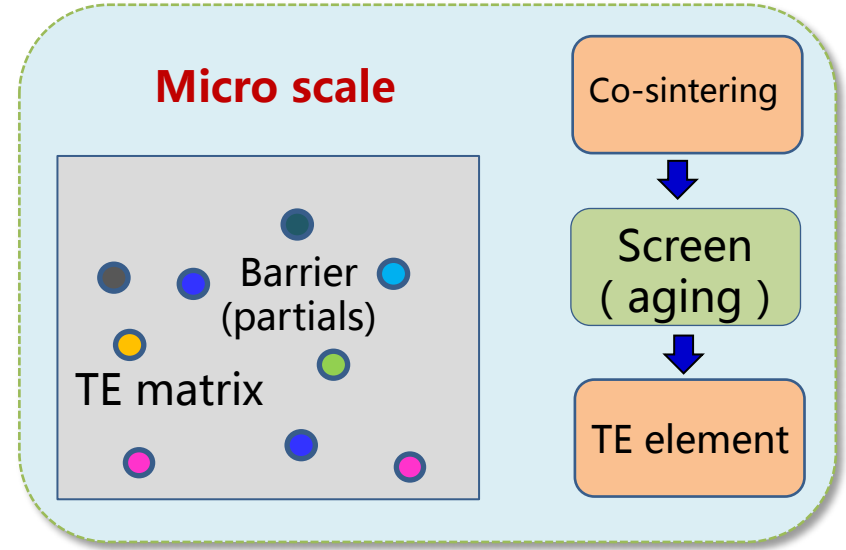


# high throughput strategy: Screen interfacial diffusion barrier

## Traditional method



## High throughput strategy

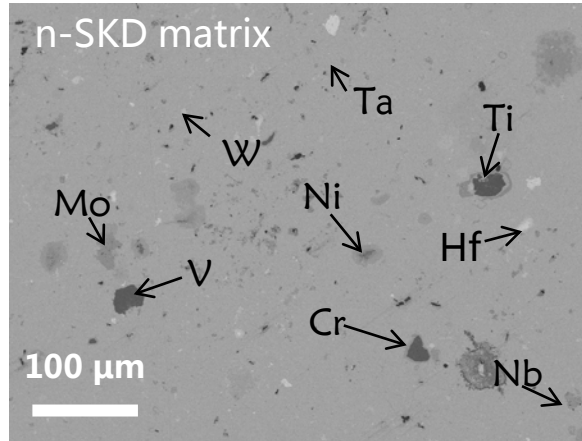


- Interface got based on the TE elements
- **High cost** in try error experiments of TE elements fabrication
- Long time of screening for one by one selection: **months ~ years**

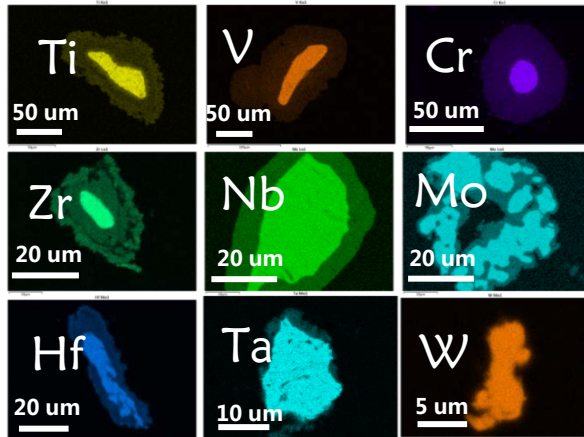
- Interface got **NOT** based on the TE elements
- **Low cost** in try error experiments of TE elements fabrication
- Short time of screening for one-time selection: **weeks**



# high throughput strategy: Screen interfacial diffusion barrier



650°C × 2 days

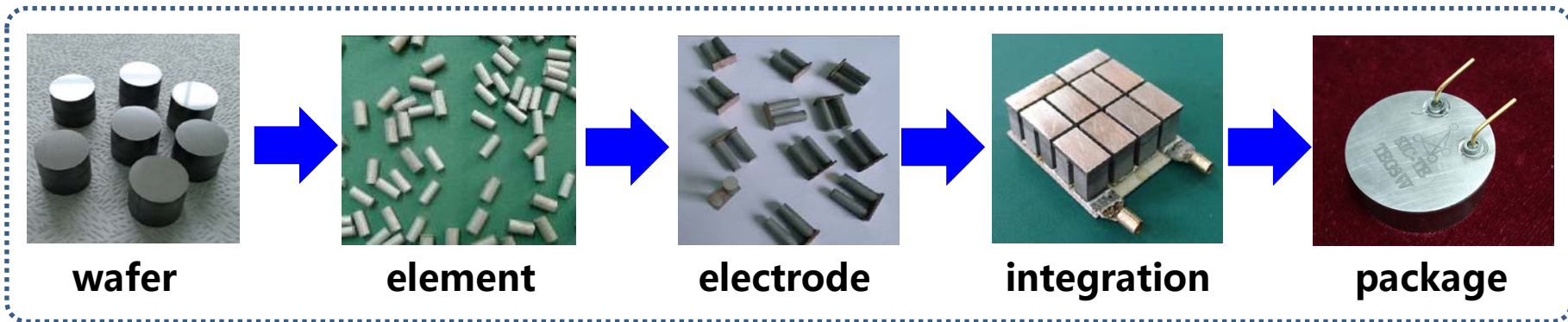


Barrier layer		Diffusion layer (650°C, 2D)	
Element	CTE/ppm	Content	Thickness/μm
V	8.3	VSb(?)	~50
Cr	6.2	CrSb ?	~40
Ti	8.4	TiSb, TiSb <sub>2</sub> , TiCoSb	~30
Zr	5.8	ZrSb <sub>2</sub>	~20
Hf	5.9	HfSb <sub>2</sub> HfCoSb	~15
Mo	5.4	Mo <sub>3</sub> Sb <sub>7</sub>	~10
Nb	7.0	NbSb <sub>2</sub>	< 10
Ta	6.6	TaSb <sub>2</sub> TiCoSb	~5
W	4.6	N/A	N/A

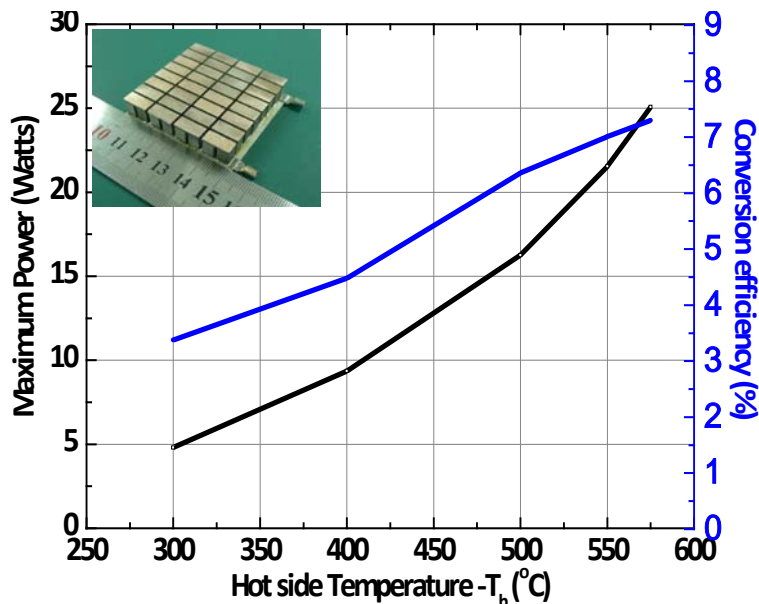
\* Cost and fabrication technique should be considered in selection.

# Performance of SKD-based TE devices

## Integration of SKD module



### TYPICAL CURVES

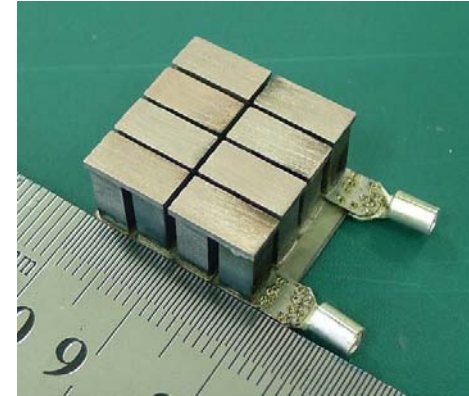


### Data sheet of SKD TE generation modules

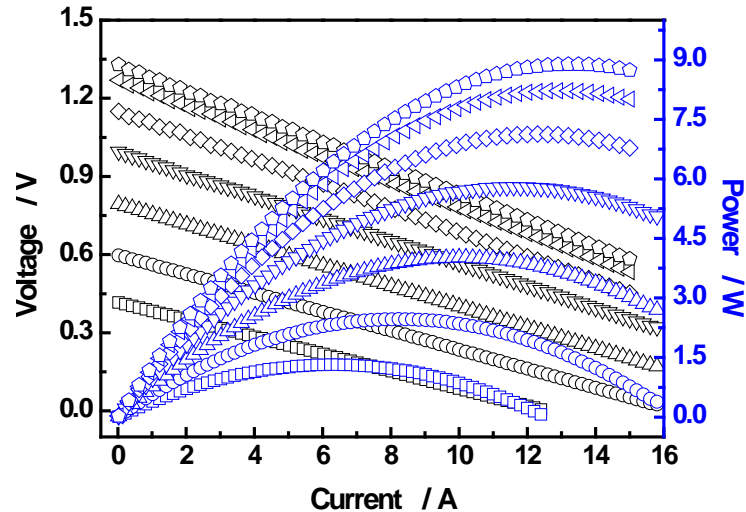
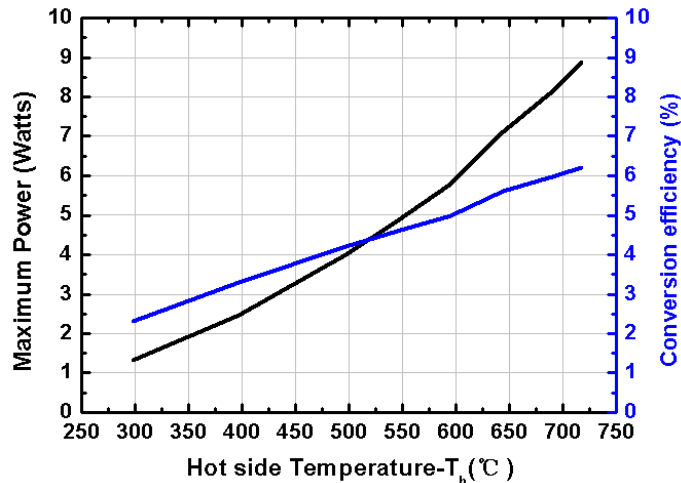
	Dimensions	Couples	Hot-side Temp. (°C)	Cold-side Temp. (°C)	$V_{oc}$ (V)	$P_{max}$ (Watt)	$R_{Inter.}$ (mΩ)
TEG5	Module Size: 20×20×10mm <sup>3</sup>	8	400	25	0.80	1.97	82
	Dice Size: 4×4×8 mm <sup>3</sup>		500	30	1.06	3.30	85
			600	35	1.31	4.09	87
TEG10 (H-V)	Module Size: 30×30×10 mm <sup>3</sup>	18	400	35	1.50	3.85	139
	Dice Size: 4×4×8 mm <sup>3</sup>		500	40	1.77	5.72	142
			600	45	2.17	7.53	157
TEG10 (L-V)	Module Size: 30×30×10 mm <sup>3</sup>	10	400	30	0.83	3.74	47
	Dice size: 6×4.5×8 mm <sup>3</sup>		500	35	1.11	6.33	48
			600	40	1.24	7.86	49
TEG25	Module Size: 50×50×10 mm <sup>3</sup>	32	400	40	2.62	9.37	180
	Dice Size: 5×5×8 mm <sup>3</sup>		500	50	3.52	16.25	188
			575	65	4.43	25.08	193

# Performance of HH-based TE devices

- ❑ Pb-free TE modules using HH alloys
- ❑ Capability of working at **700 °C** (hot side)
- ❑ Output power up to **9 Watts** ( $\Delta T= 650^\circ\text{C}$ )
- ❑ Efficiency up to **6.2% @  $\Delta T= 650^\circ\text{C}$**
- ❑ Dimensions: **20mm × 20mm × 10mm(H)**
- ❑ Output power density up to **2.2 W/cm<sup>2</sup>**



\* HH materials provided by Prof. Tiejun Zhu (Zhejiang University)



	Th	Tc	P <sub>max</sub>	P <sub>conver.</sub>
—□	299	32	1.32	2.3
—○	398	39	2.47	3.3
—△	497	46	4.01	4.2
—▽	595	54	5.80	5.0
—◇	645	57	7.12	5.6
—◁	694	61	8.22	6.0
—◊	718	63	8.89	6.2

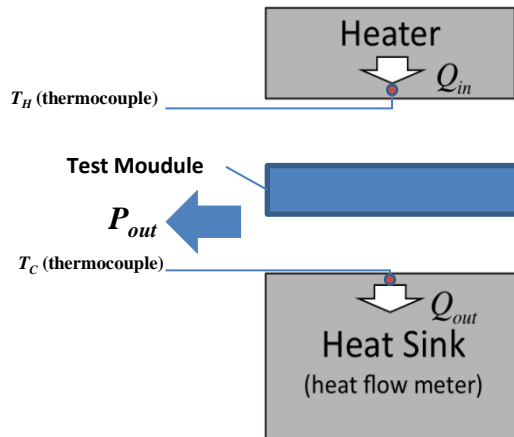
# TEG module testing

1. Agreement found in Electrical measurement of TE devices.
2. Significant measurement issues observed in heat flow measurement.
3. Measurement standard not established.

**Including:**  $T_h$  &  $T_c$ , gas pressure, uniaxial pressure;

Vaccum pump on/off during testing;

Scanning mode (scanning speed, temperature stage, .....)



**Definition of efficiency:**

$$\eta = \frac{P_{out}}{Q_{in}} \times 100\% = \frac{P_{out}}{Q_{out} + P_{out}} \times 100\%$$



**ULVAC-RIKO:PEM-2**



**Module testing system in AIST**

# Testing standard of TEG materials and modules

## Annex VIII Participants

- **IEA-AMT Thermoelectric Annex**

- Annex lead: Oak Ridge National Laboratory (H. Wang)
- USA: GMZ (G. Joshi); Marlow (J. Sharp); GM R&D (J. Salvador); Army Research Laboratory (P. Taylor), NIST (J. Martin)
- China: SICCAS (S.Q. Bai, L. Chen)
- Canada: CANMET(Y.C. Tseng); University of Waterloo (H. Kleinke);
- Germany: Fraunhofer IPM (J. König )
- United Kingdom: NPL (A. Cuenat)
- Korea: Korea Electrotechnology Research Institute (H.W. Lee)



- **IEA-AMT members countries:**

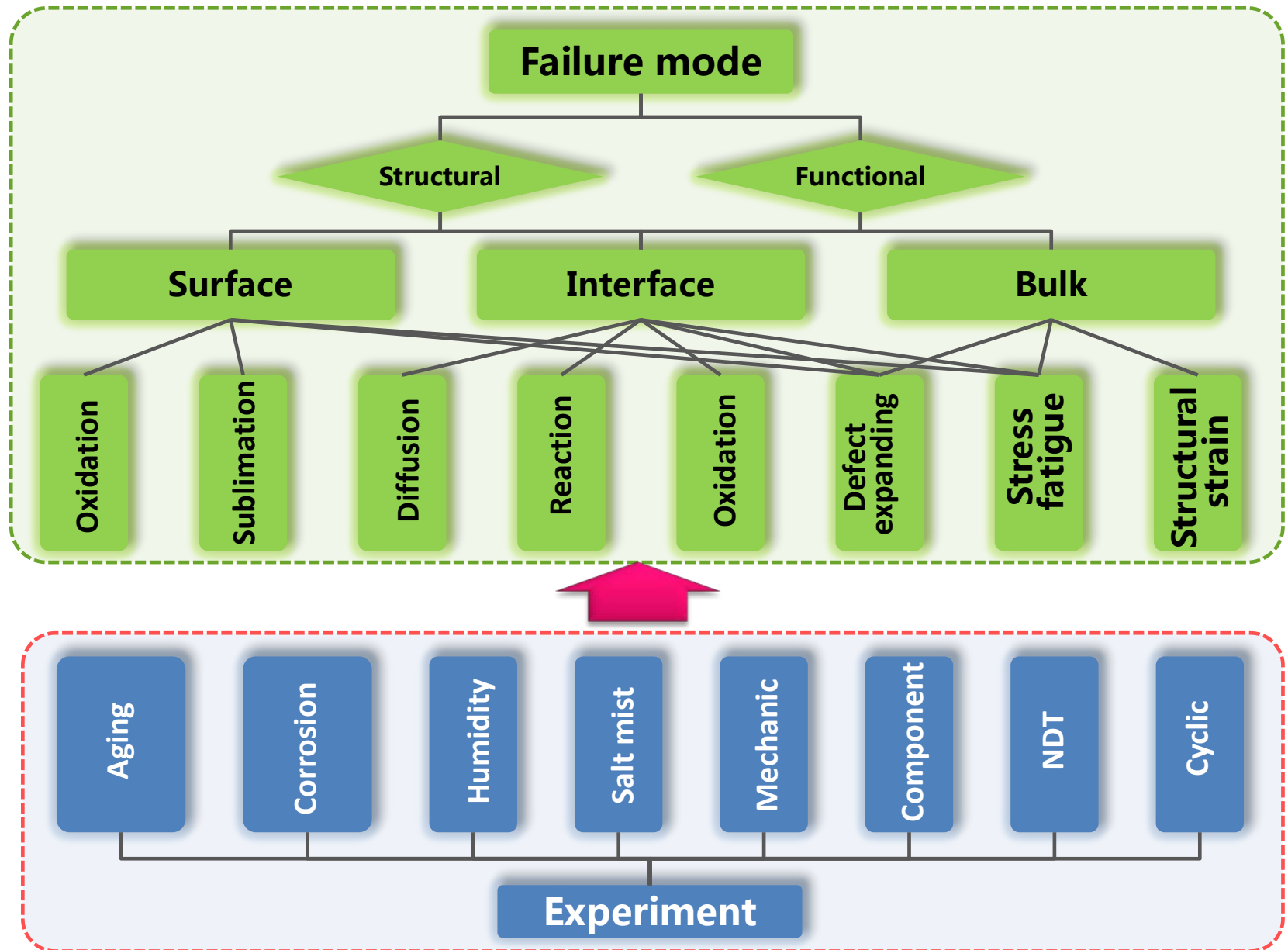
- Finland: VTT
- Israel:
- Australia:



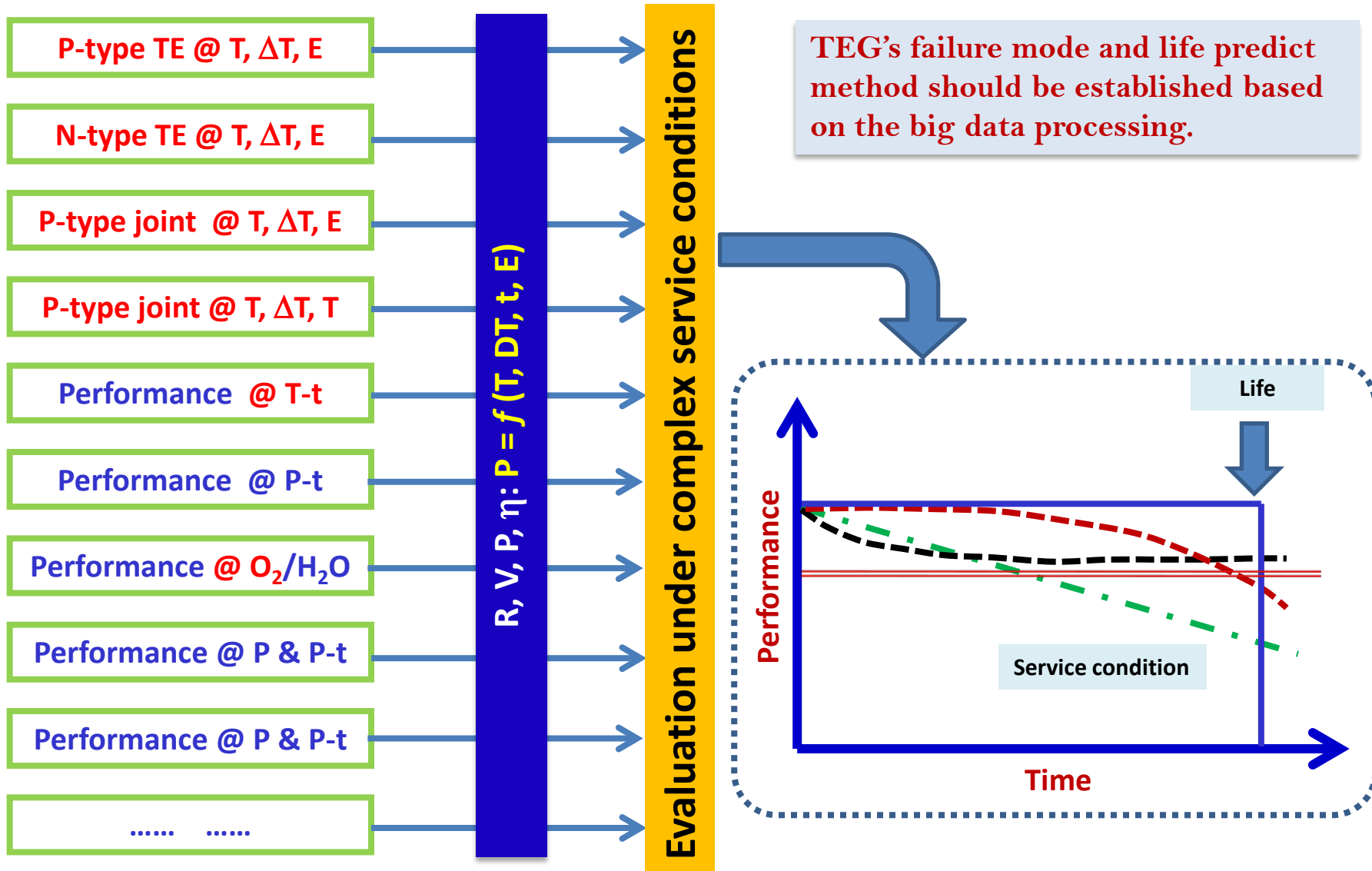
*This project is supported by the International Energy Agency (IEA) under the Implementing Agreement on Advanced Materials for Transportation (AMT)*



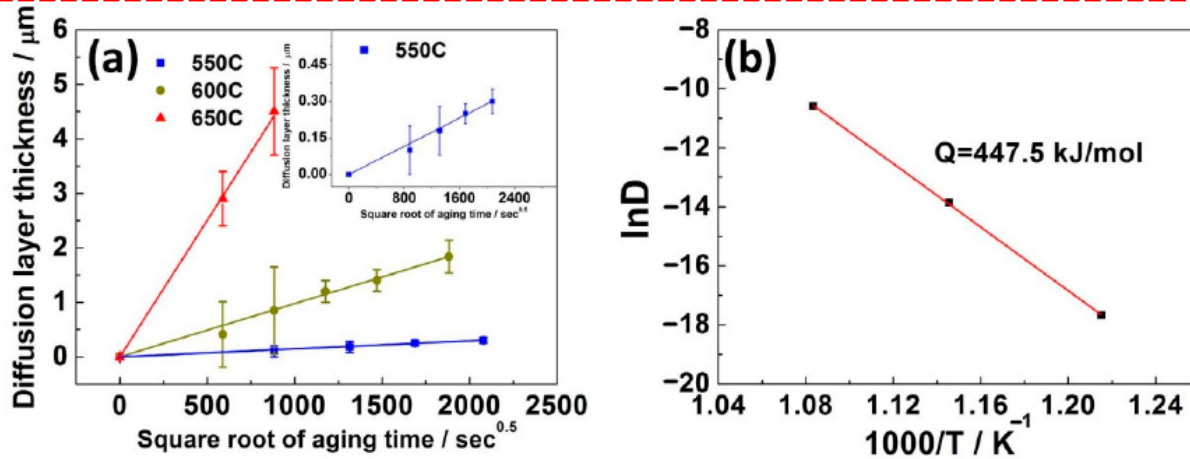
# TEG module failure mode & service behavior



# TEG module failure mode & service behavior



# Life predict based on thermal dynamics

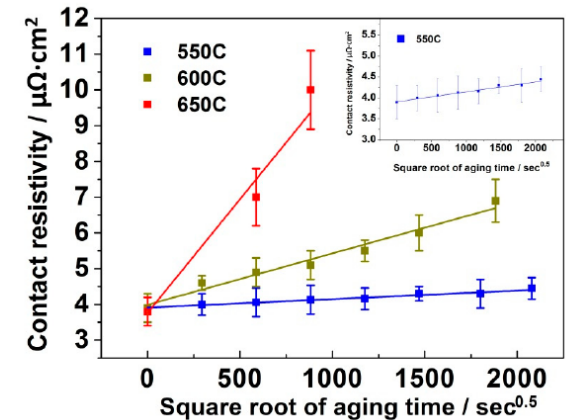


Temperature/ $^{\circ}\text{C}$	$D/10^{-19} \text{ m}^2/\text{s}$	$Y/\mu\text{m}$
550	0.21	$1.45 \times 10^{-4} \cdot t^{0.5}$
600	9.53	$9.76 \times 10^{-4} \cdot t^{0.5}$
650	251	$50.1 \times 10^{-4} \cdot t^{0.5}$

## Arrhenius equation:

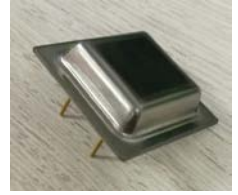
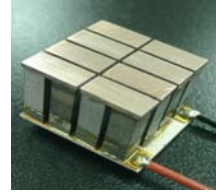
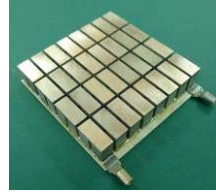
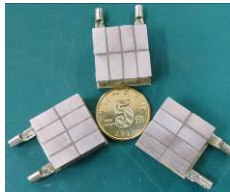
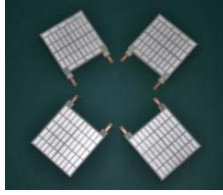
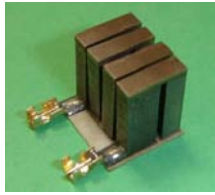
$$Y - Y_0 = (Dt)^{0.5}$$

$$D = D_0 \exp\left(-\frac{Q}{RT}\right)$$



## Life predict based on the interfacial resistivity

Temperature/ $^{\circ}\text{C}$	Contact Resistivity/ $\mu\Omega \cdot \text{cm}^2$	Predicted Service Life (a)/day	Predicted Service Life (b)/day
550	$2.37 \times 10^{-4} \cdot t^{0.5} + 3.91$	7642	53,346
600	$14.1 \times 10^{-4} \cdot t^{0.5} + 3.99$	201	1431
650	$63.5 \times 10^{-4} \cdot t^{0.5} + 3.76$	11	75



**Thank you for your attention !**

